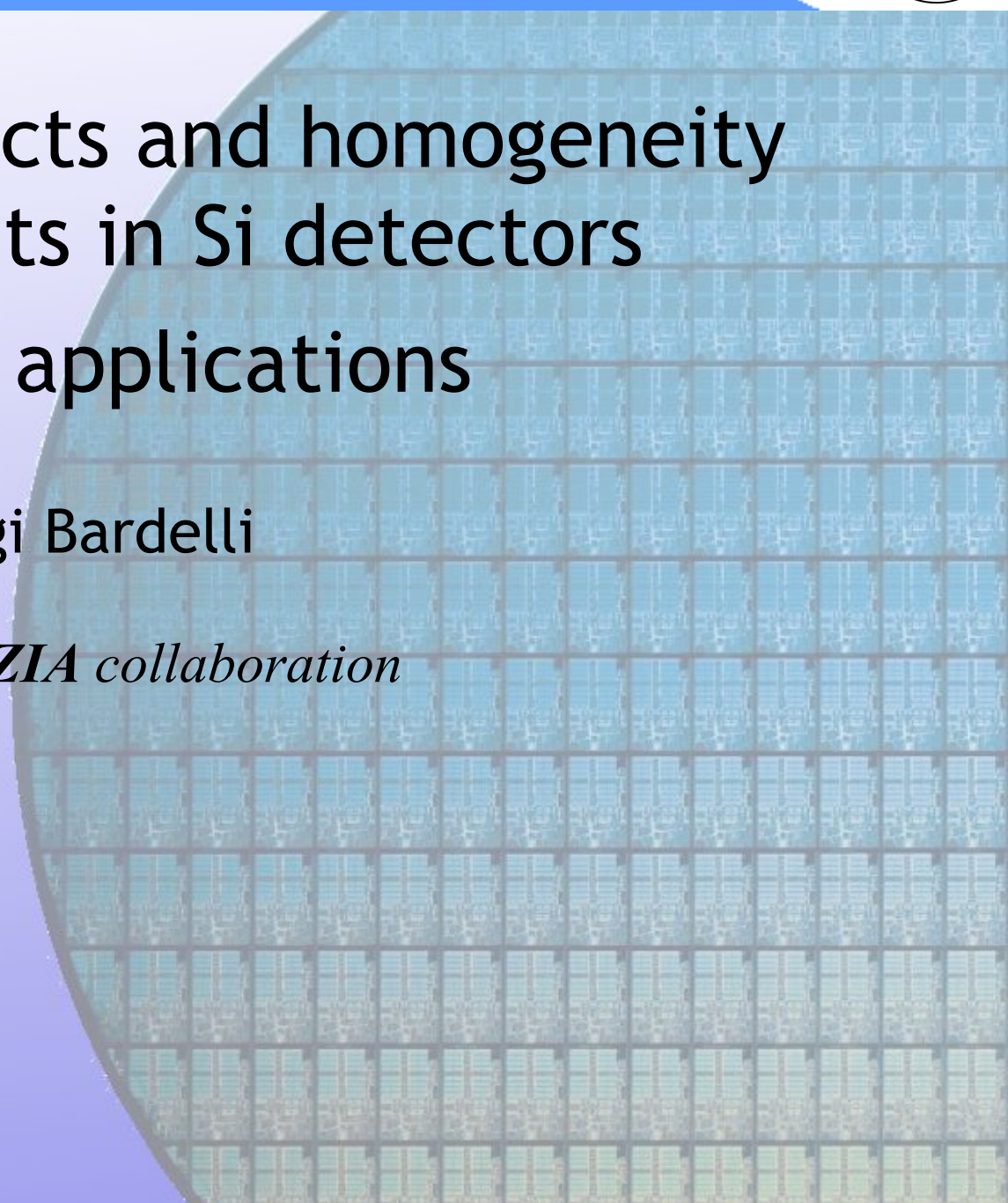
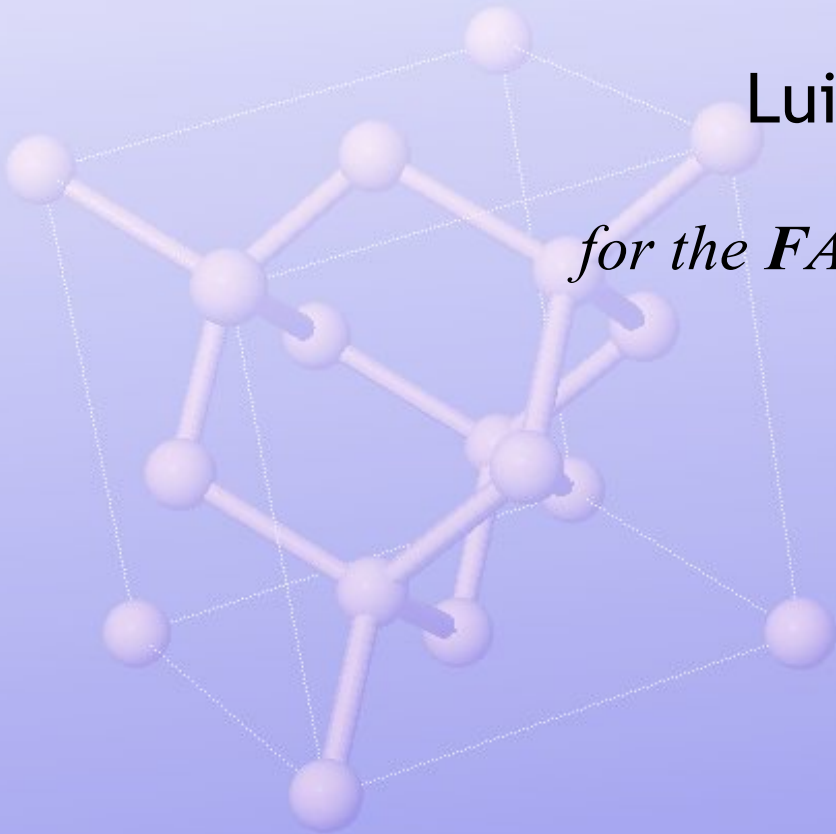


Channeling effects and homogeneity measurements in Si detectors for PSA applications

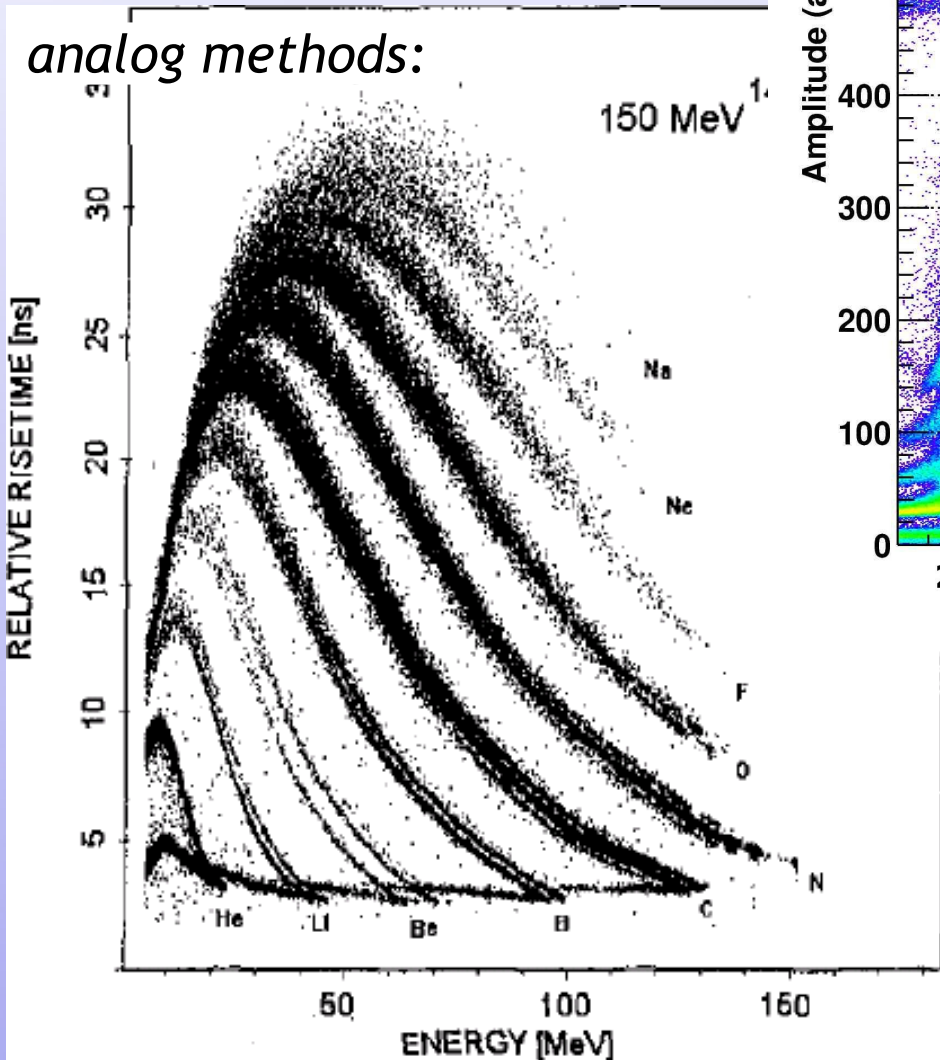
Luigi Bardelli

for the FAZIA collaboration

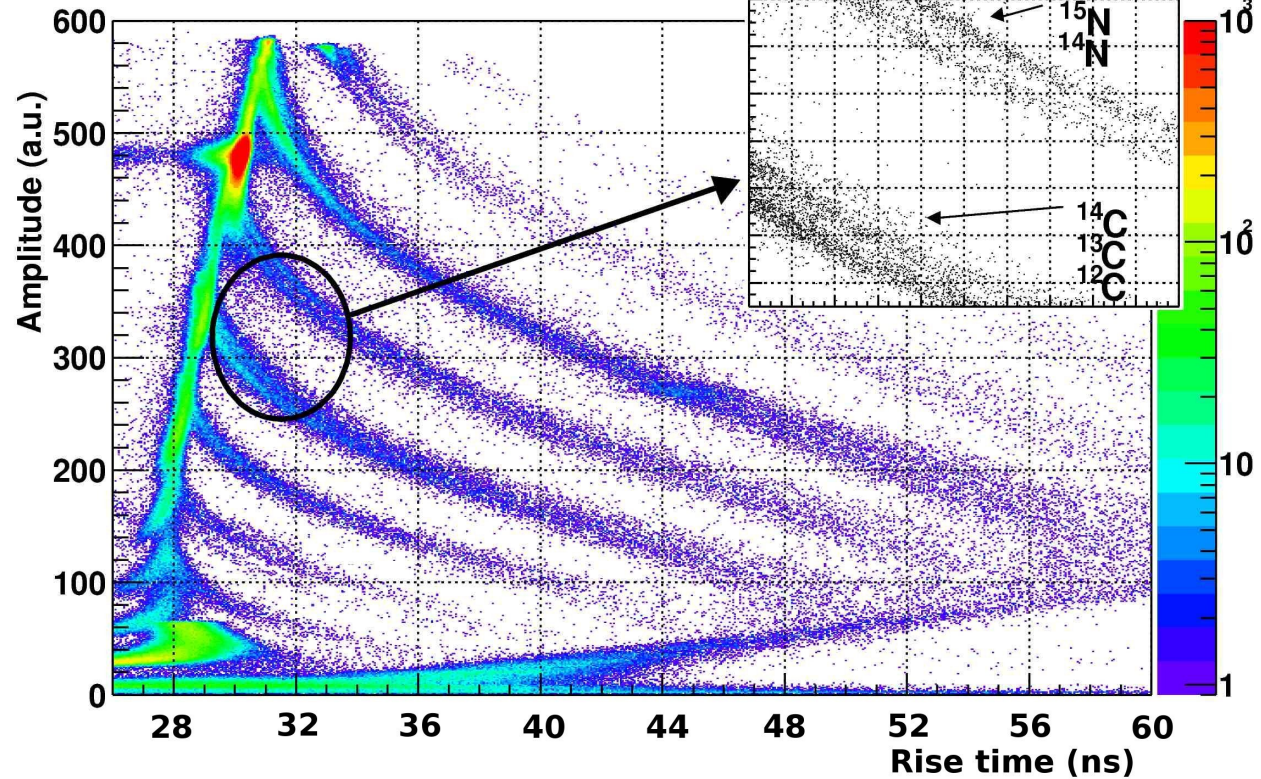


- Homogeneity:
 - A PSA-based method for resistivity measurements
 - Results
- Channeling:
 - Introduction
 - The silicon crystal structure
 - Experimental results
 - How to “avoid” channeling
- Results from recent FAZIA collaboration PSA tests

Standard energy vs. "risetime" plots:



digital methods:



L. Bardelli et al, Nucl. Phys. A 746 (2004) 272
(12 bit, 100 MSamples/s digitizer + digital signal processing dCFD)

M. Mutterer et al, IEEE Trans. Nucl. Science, vol. 47 no. 3, 2000
(2 ways fast analog shaping + timing)

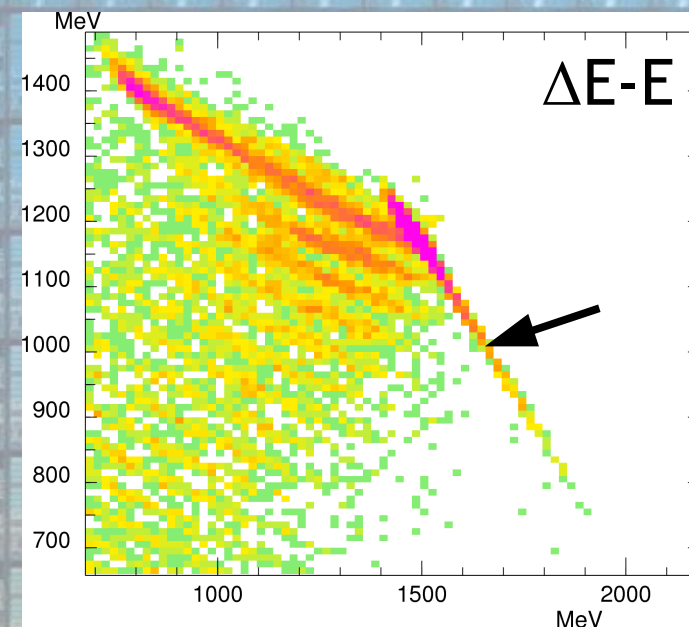
Regardless of the used analysis method (whether analog or digital) the detector properties can play a significant role in the final identification properties:



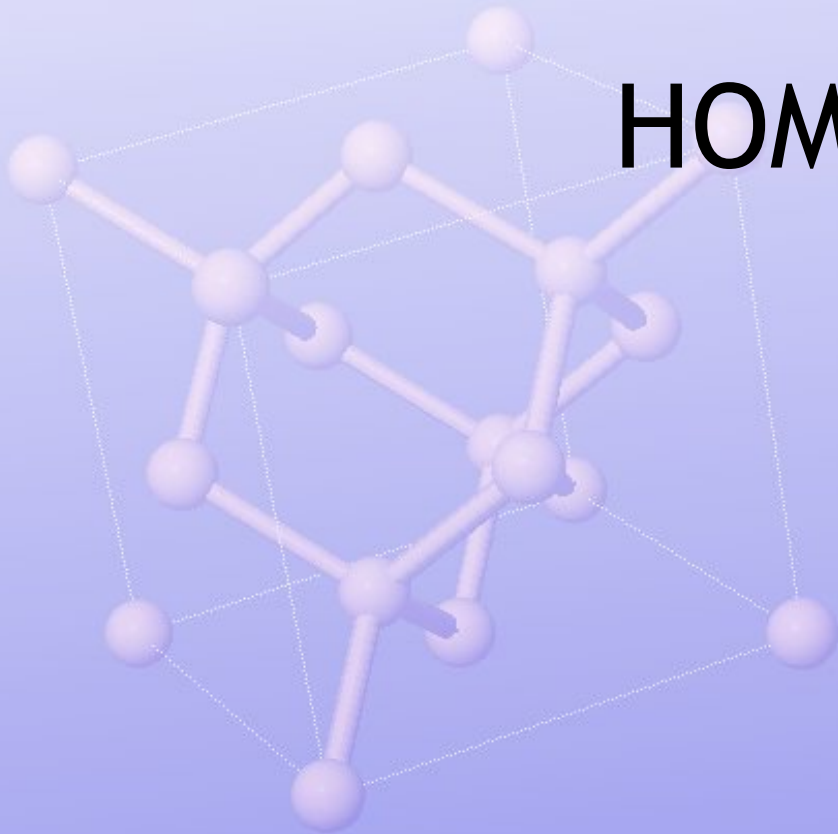
- resistivity homogeneity
- thickness homogeneity
- dead-layers
- (etc etc)

What about the silicon **crystal structure**, i.e. channeling effects?

NOTE: channeling is a well known issue in industry for ion implantation applications (microelectronics), transmission detectors (DE-E) and high energy physics, but it is not (yet) studied for PSA

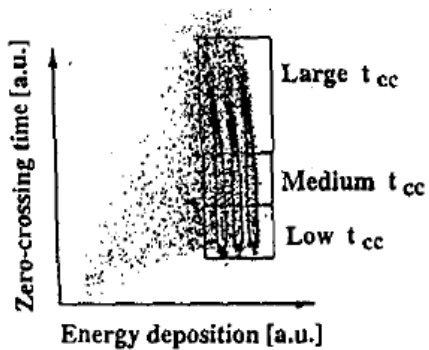


HOMOGENEITY

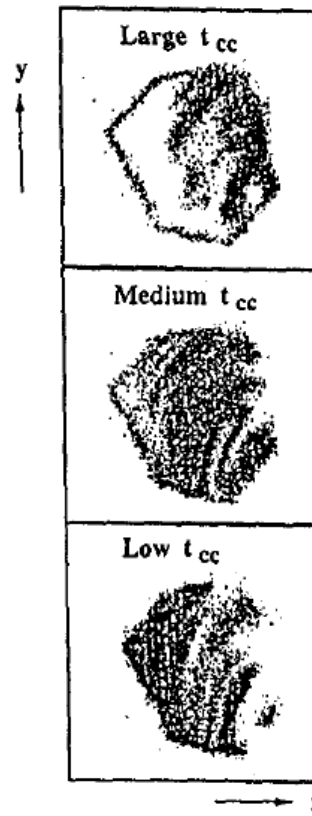


It is well known that any non-homogeneity in the electric field inside the detector may have a severe impact over the PSA discrimination capabilities:

a) t_{cc} gates:



b) Maps of a single detector:



c) Combined maps of detectors from a single Si wafer (medium t_{cc}):



Is it possible to measure the resistivity and/or doping homogeneity of our detectors?

(non destructive is better.....)

G.Paush et al, IEEE NS 44, v3
1997, 1040

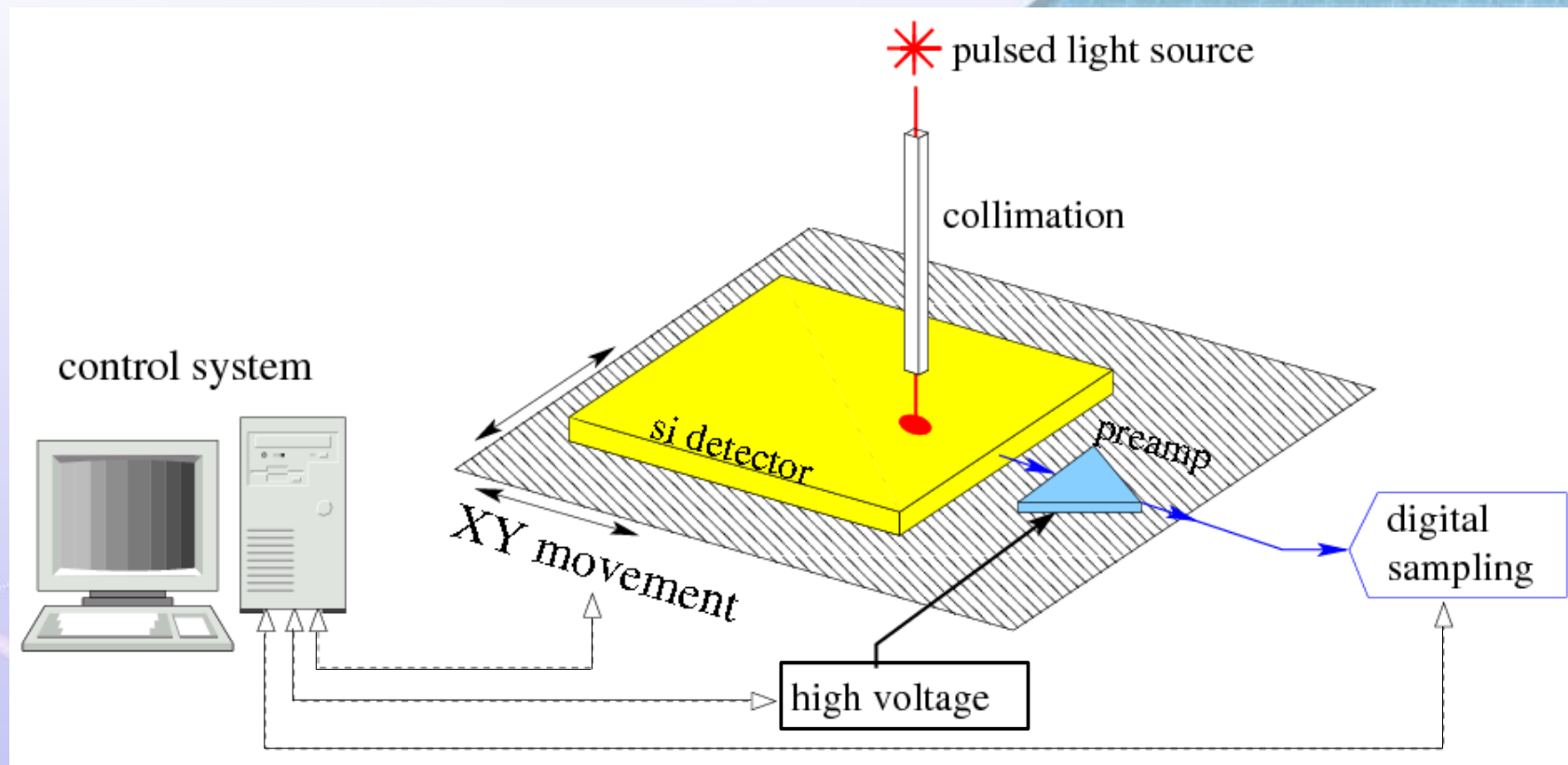
Once the detector thickness is known, the depletion voltage provides a direct measurement of the material resistivity:

$$\rho = \frac{th^2}{2 V_D \epsilon_R \mu}$$

Depletion voltage measurements are routinely performed with C-V plots.

Can we do something like that as a function of the position on the detector?

(and without the need of particular strip or pixel readout)



The detector is mounted on a XY movement.

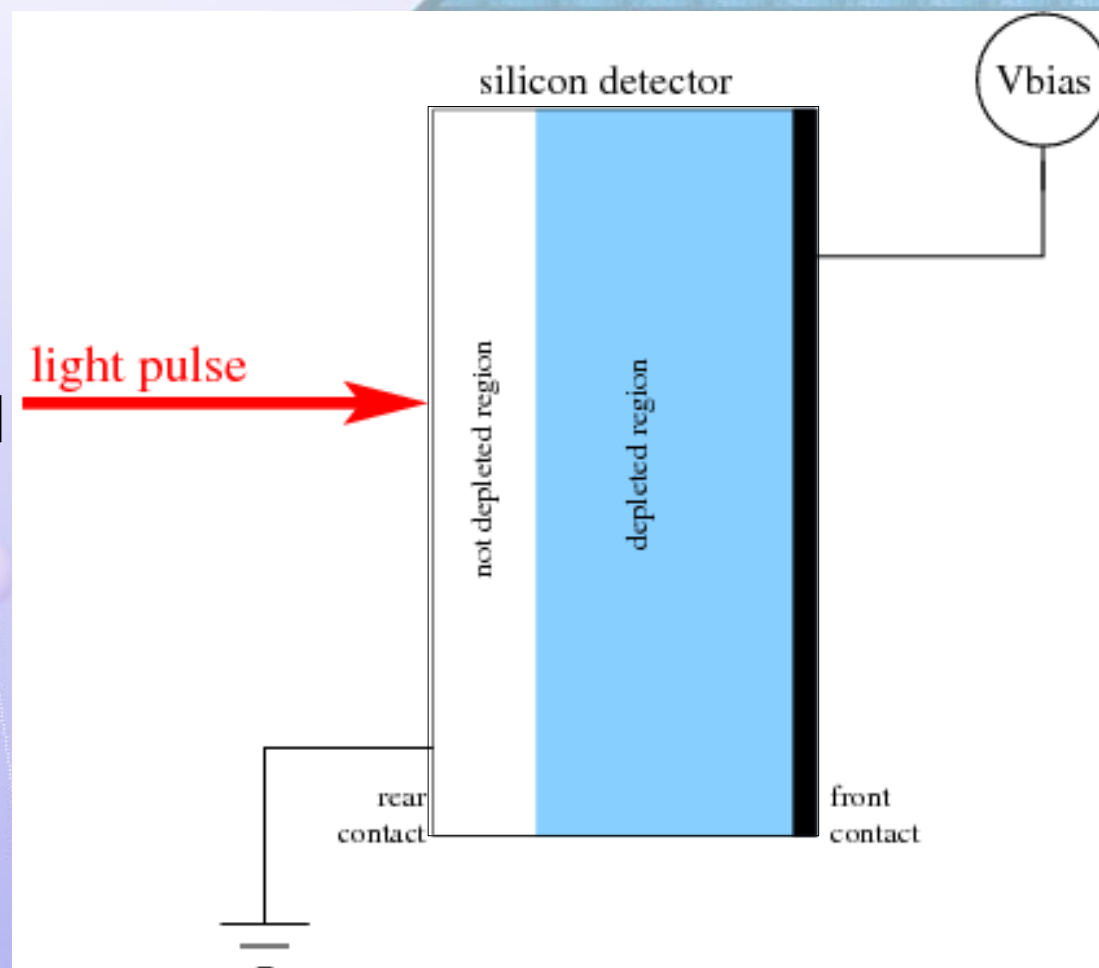
Both the XY support and the HV are computer controlled.

Shapes are collected with a digitizer (Florence DSP card)

The collimated laser pulse enters the detector in the low field zone.

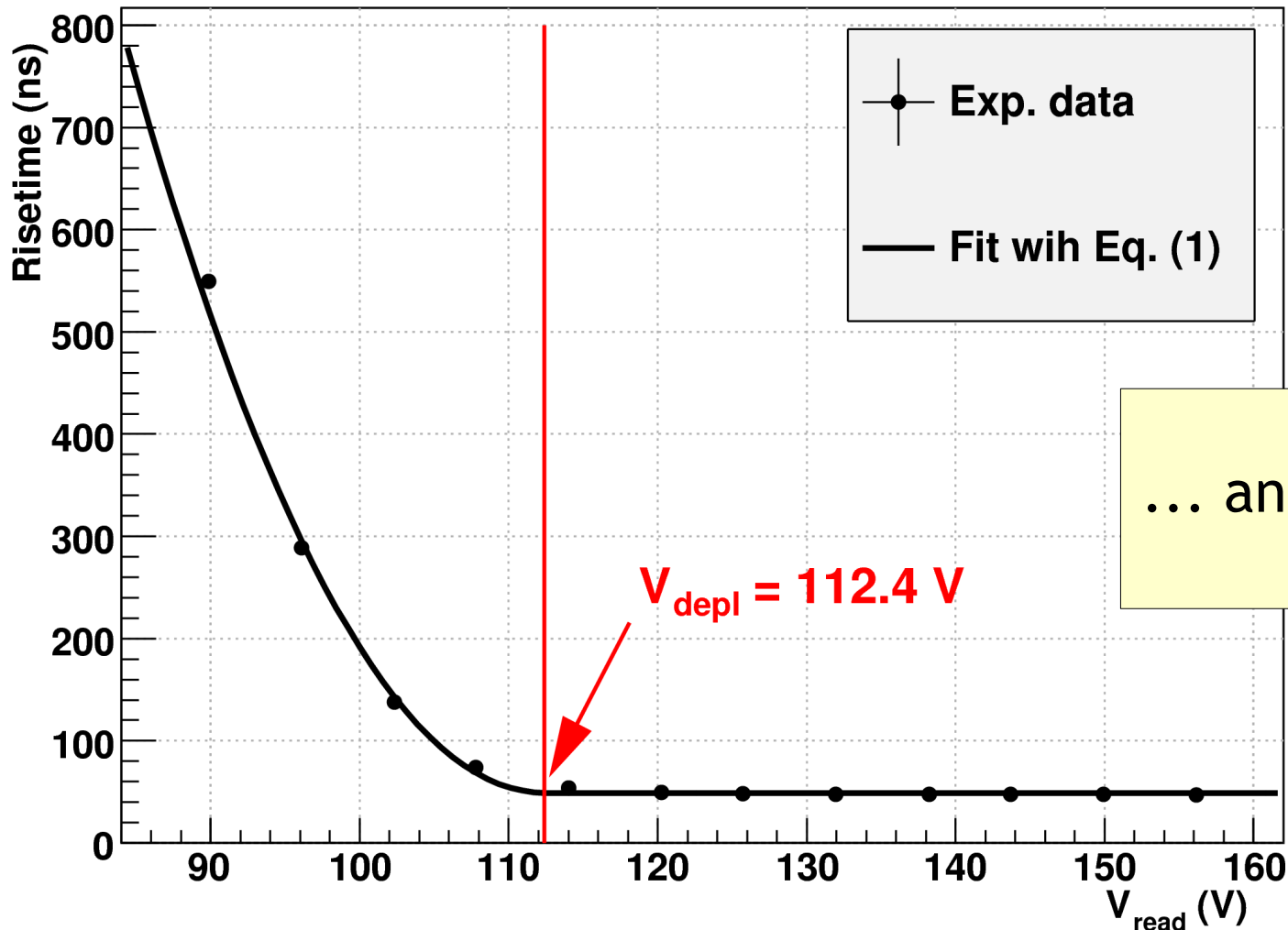
Shapes are collected for various applied voltages and various XY positions.

We make a XY and V_{applied} scan of the detector



For each XY position on the detector we can build an “Average risetime” vs “V_{applied}” plot:

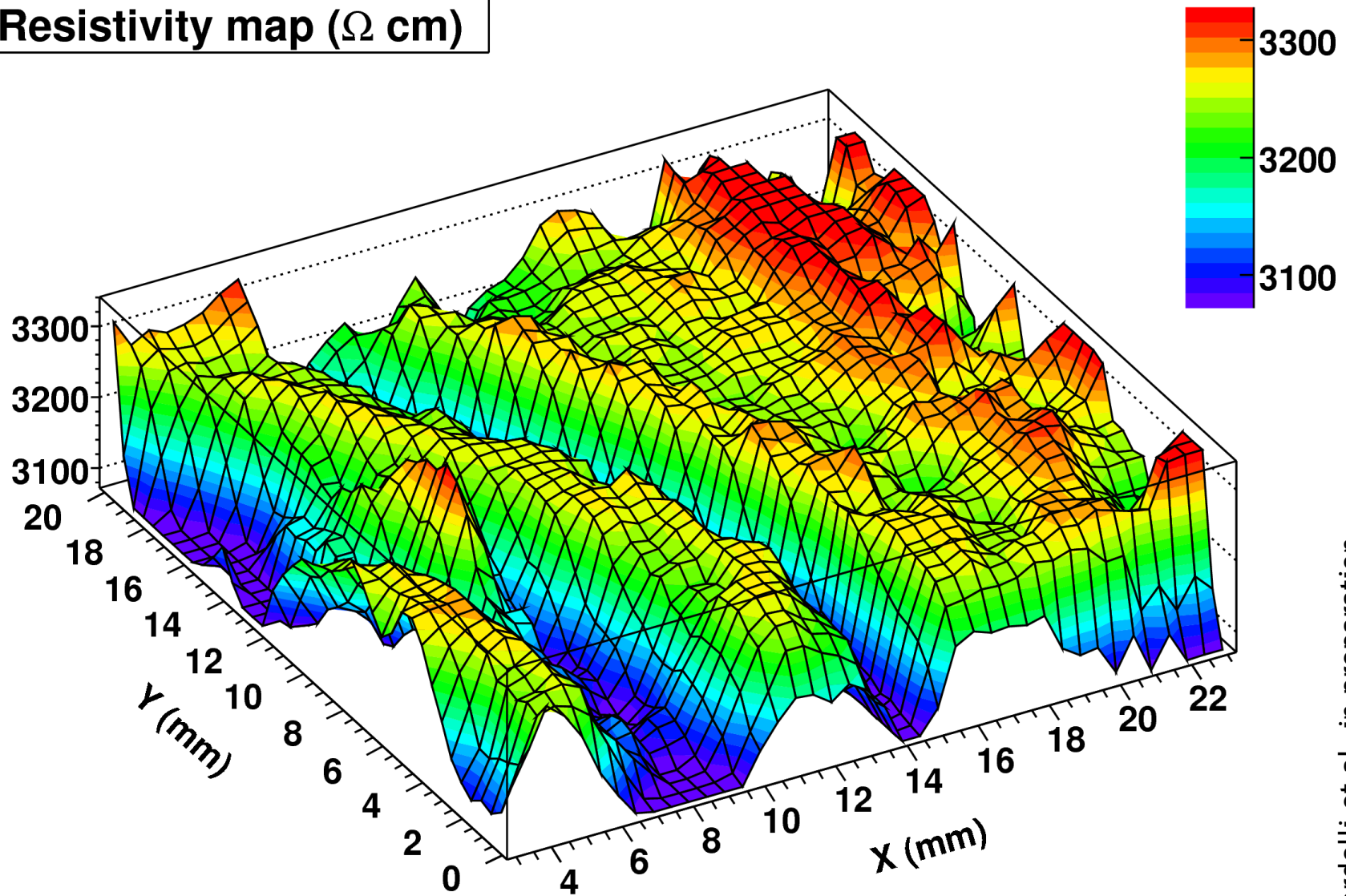
Det.70965: profile for x=2.0 y=7.0



... and fit the LOCAL V_{depl}

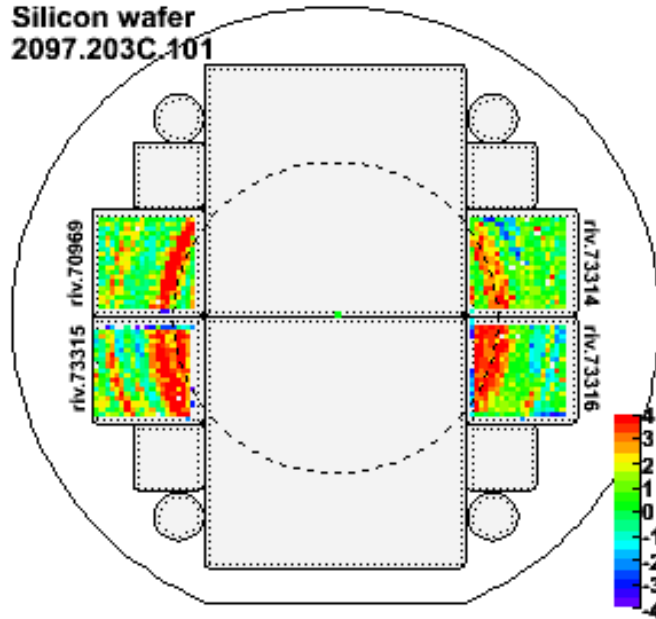
... and finally we can build a 2D resistivity plot:

Resistivity map (Ω cm)

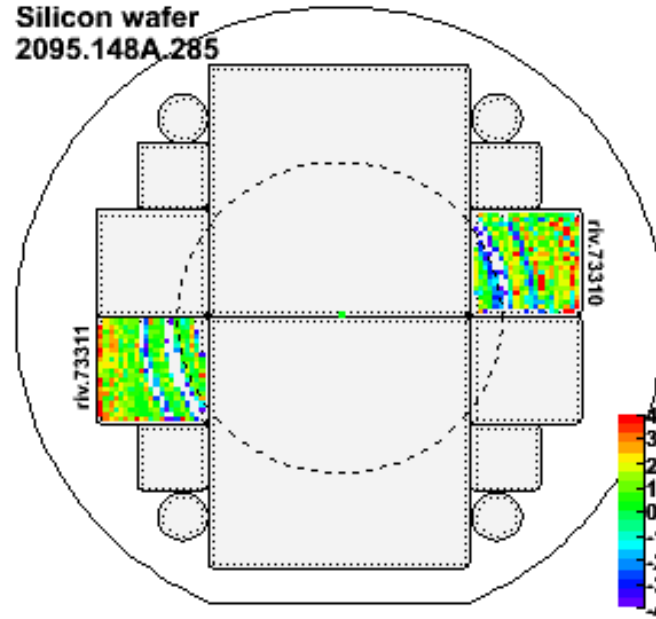


L. Bardelli et al, in preparation

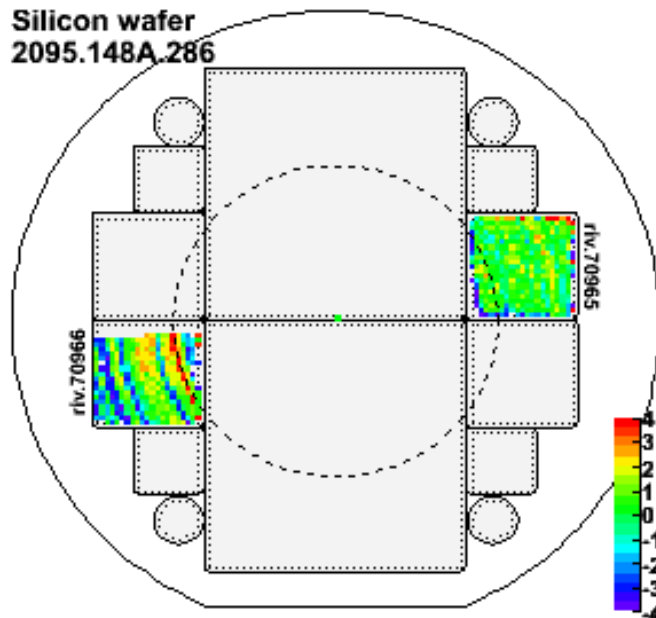
Silicon wafer
2097.203C.101



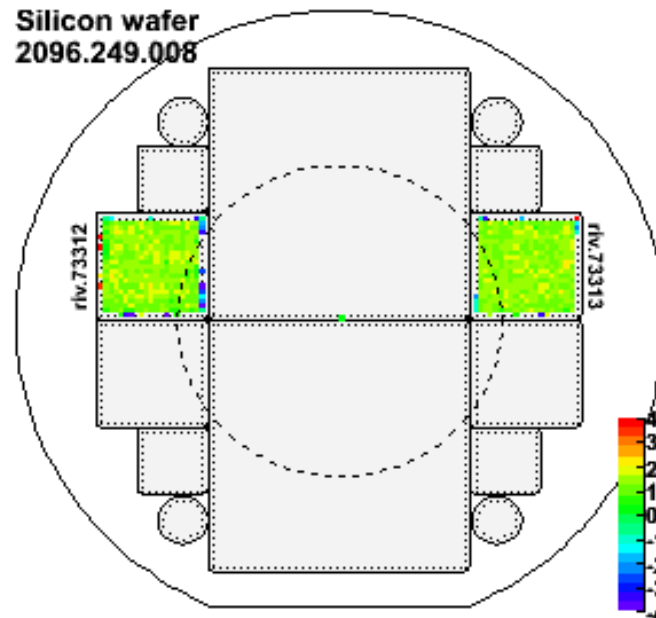
Silicon wafer
2095.148A.285



Silicon wafer
2095.148A.286



Silicon wafer
2096.249.008



We can verify
the dependence on
the geometry
on the initial wafer
clear evidence of
circular “striations”

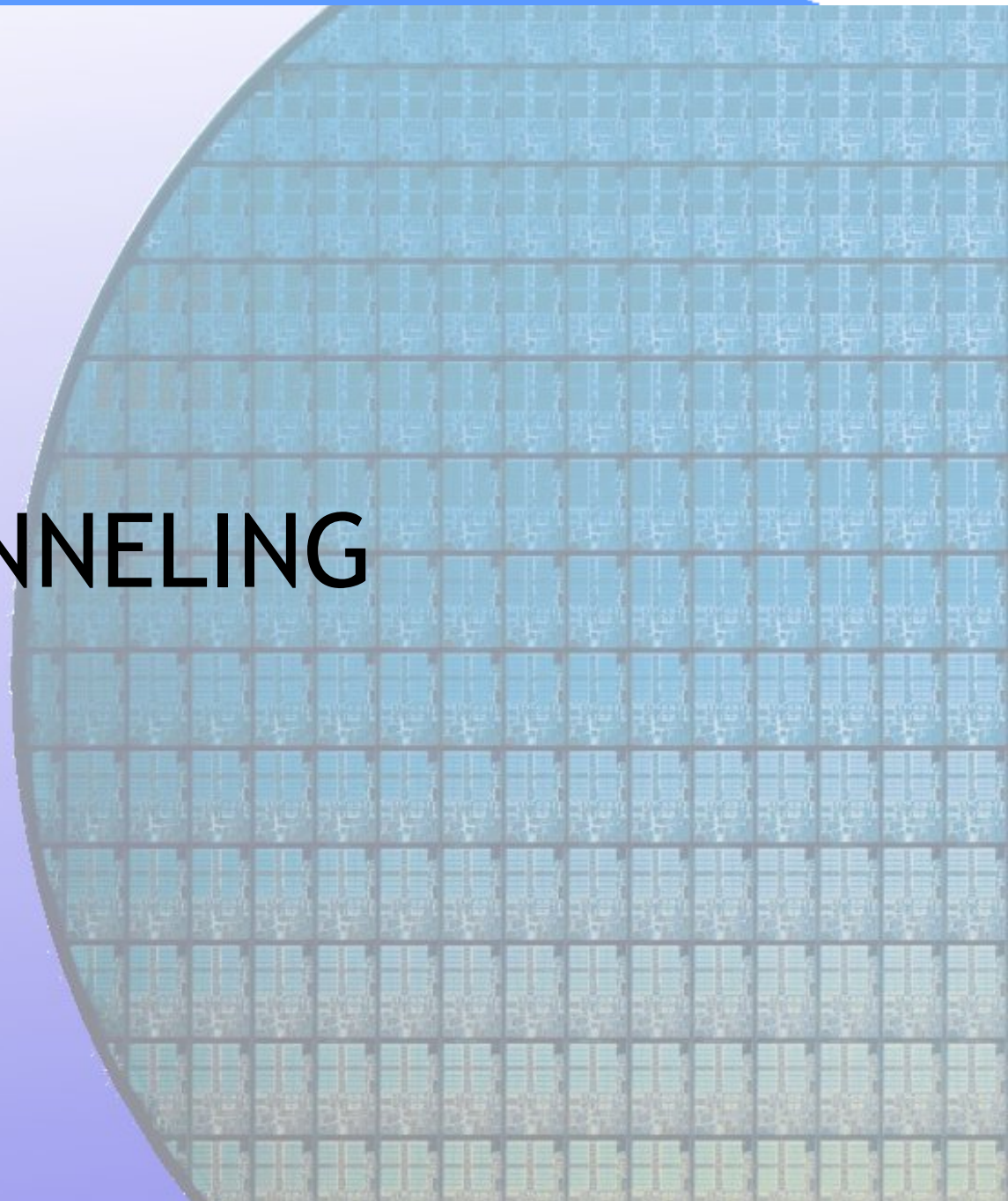
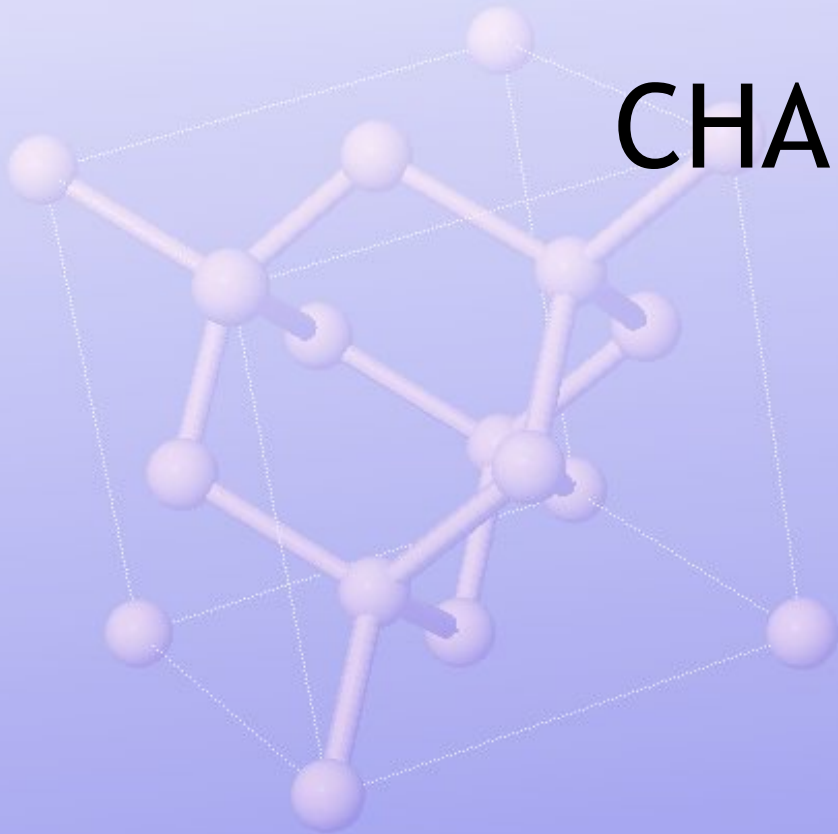
L.Bardelli et al, in preparation

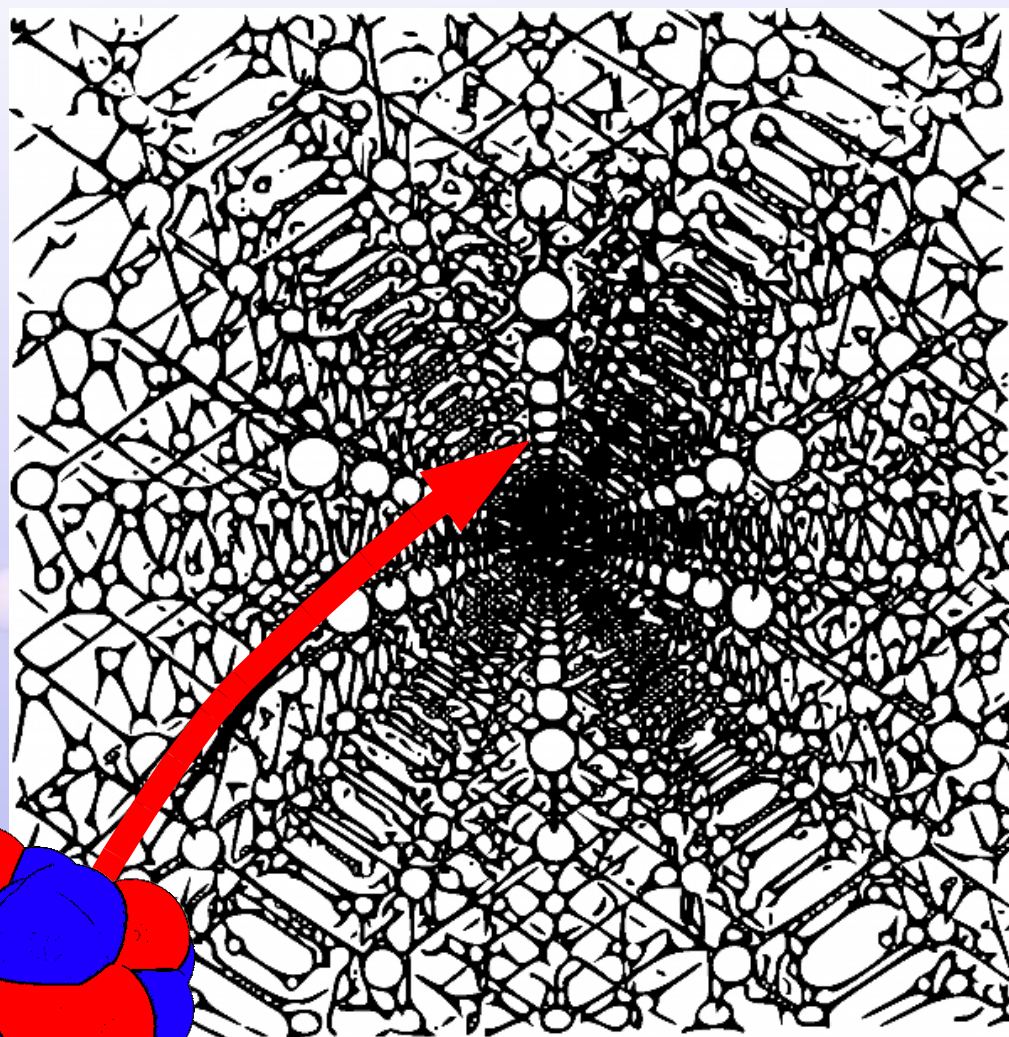
Det. Name	Thickness (um)	Nominal Vdepl (V)	Nominal Resistivity (Ohm cm)	Measured Vdepl (V)	Measured Resistivity (Ohm cm)	Non homogeneity (without border) (max-min, %)
CAN 70964	315	110	3100	120.16	2904	10.3
CAN 70965	315	110	3100	114.55	3046	4.7
CAN 70966	315	110	3100	119.02	2931	11.0
CAN 70967	516	220	4200	226.86	4128	1.7
CAN 70968	516	220	4200	227.59	4115	2.1
CAN 70969	713	150	11900	158.48	11319	7.4
CAN 73311	315	110	3100	109.40	3190	9.4
CAN 73312	516	220	4200	227.26	4124	1.3
CAN 73313	516	220	4200	227.40	4120	1.3
CAN 73314	713	150	11900	161.51	11084	8.0
CAN 73315	713	150	11900	167.95	10677	7.7
CAN 73316	713	150	11900	170.17	10524	37.6

Now we can inspect the measured non-homogeneity and choose the “best” detectors for our PSA applications!

experimental results later ...

CHANNELING





Ions tend to follow the direction between two neighboring **crystalline planes and/or axes**, but at the largest possible distance from each of them

-> they travel in the “channels” present in the material

Energy loss in an crystal (aligned configuration):

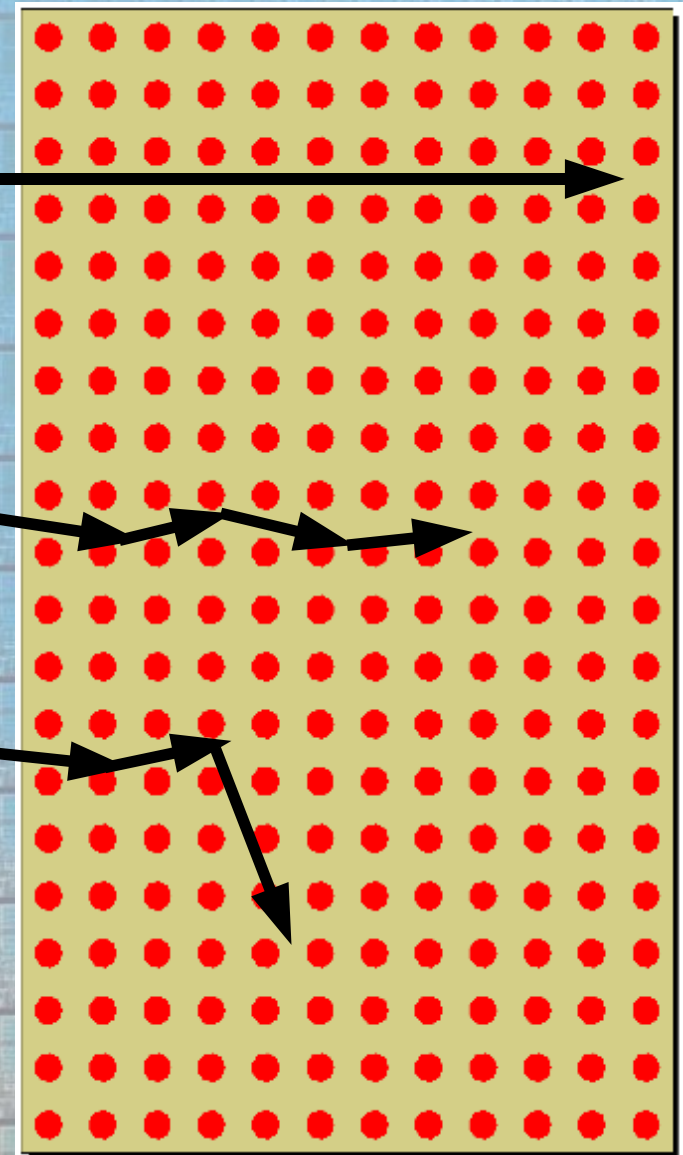
“perfect” channeling
long range, low average dE/dx

shorter range, higher average dE/dx

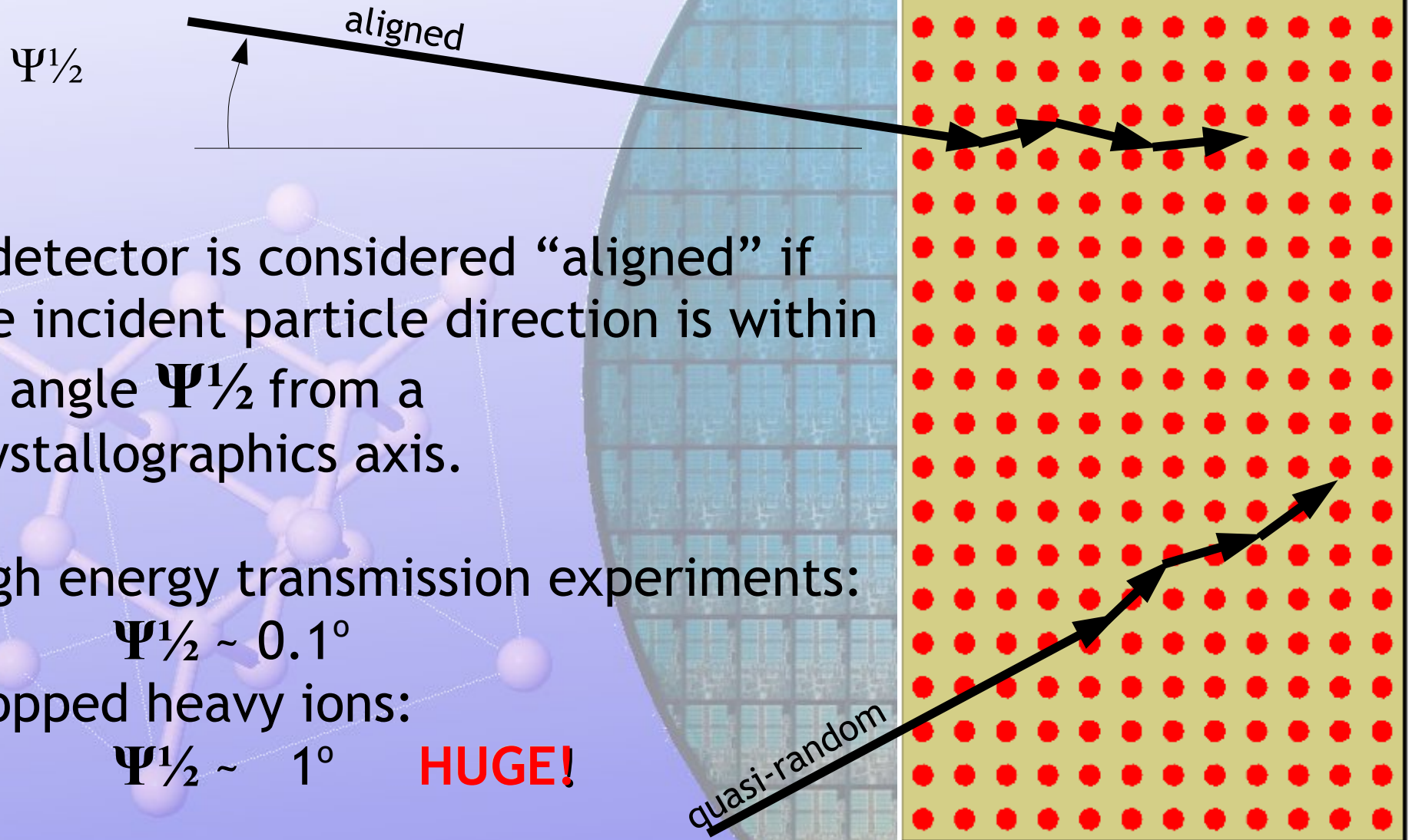
channeling + de-channeling
even shorter range, higher average dE/dx

many possible trajectories leading to
different ranges and/or average dE/dx

resolution loss!



What is the meaning of “aligned” ?



A detector is considered “aligned” if the incident particle direction is within an angle $\Psi^{1/2}$ from a crystallographics axis.

High energy transmission experiments:

$$\Psi^{1/2} \sim 0.1^\circ$$

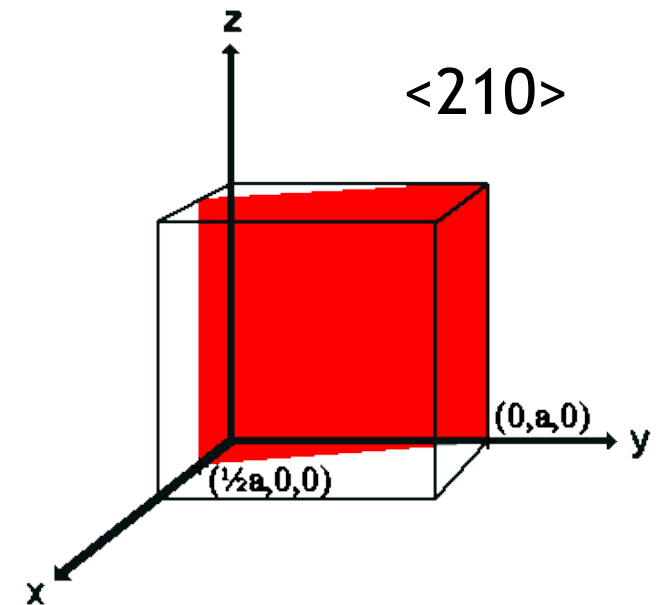
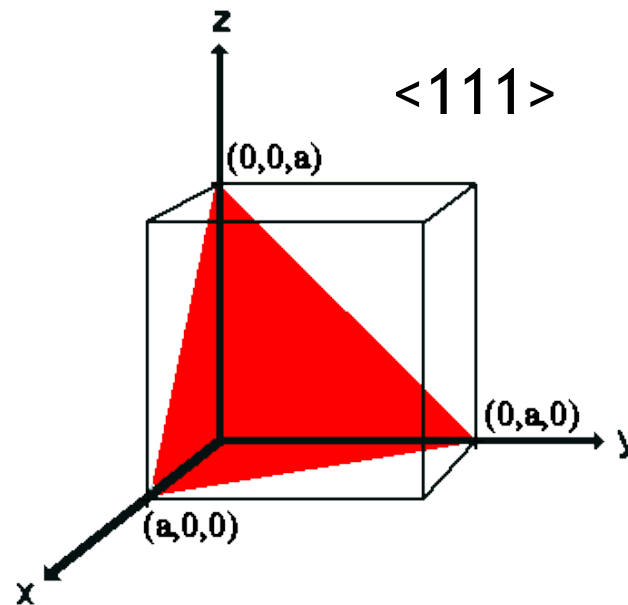
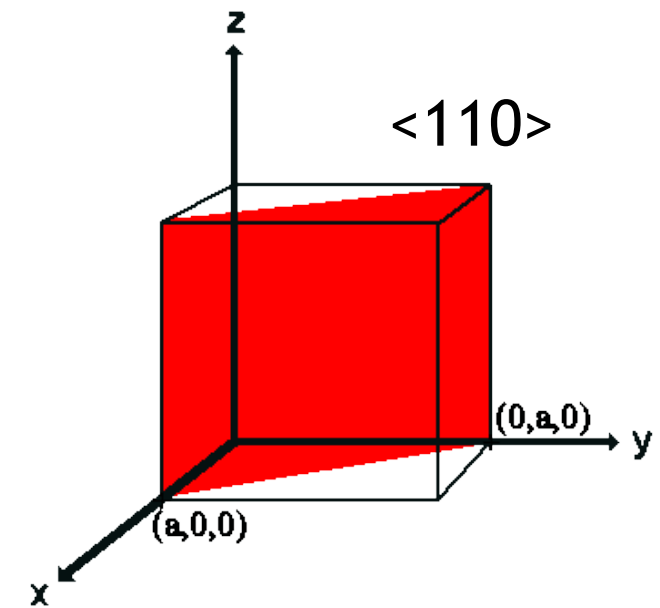
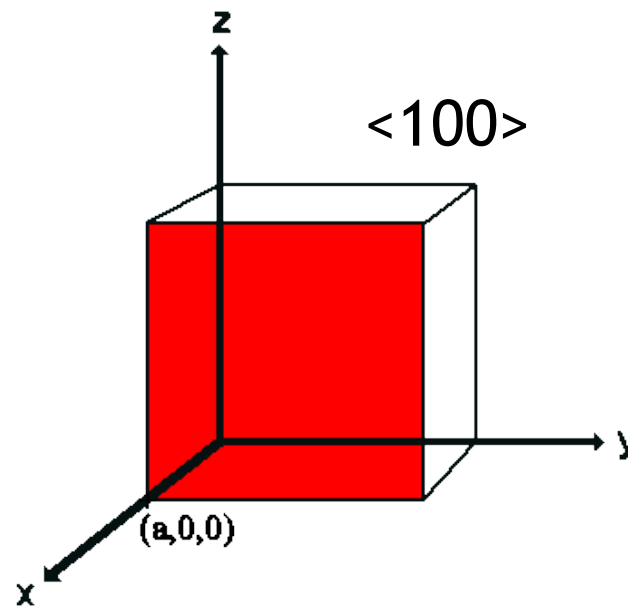
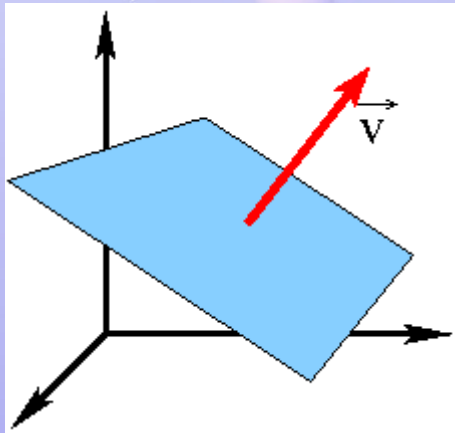
Stopped heavy ions:

$$\Psi^{1/2} \sim 1^\circ \quad \text{HUGE!}$$

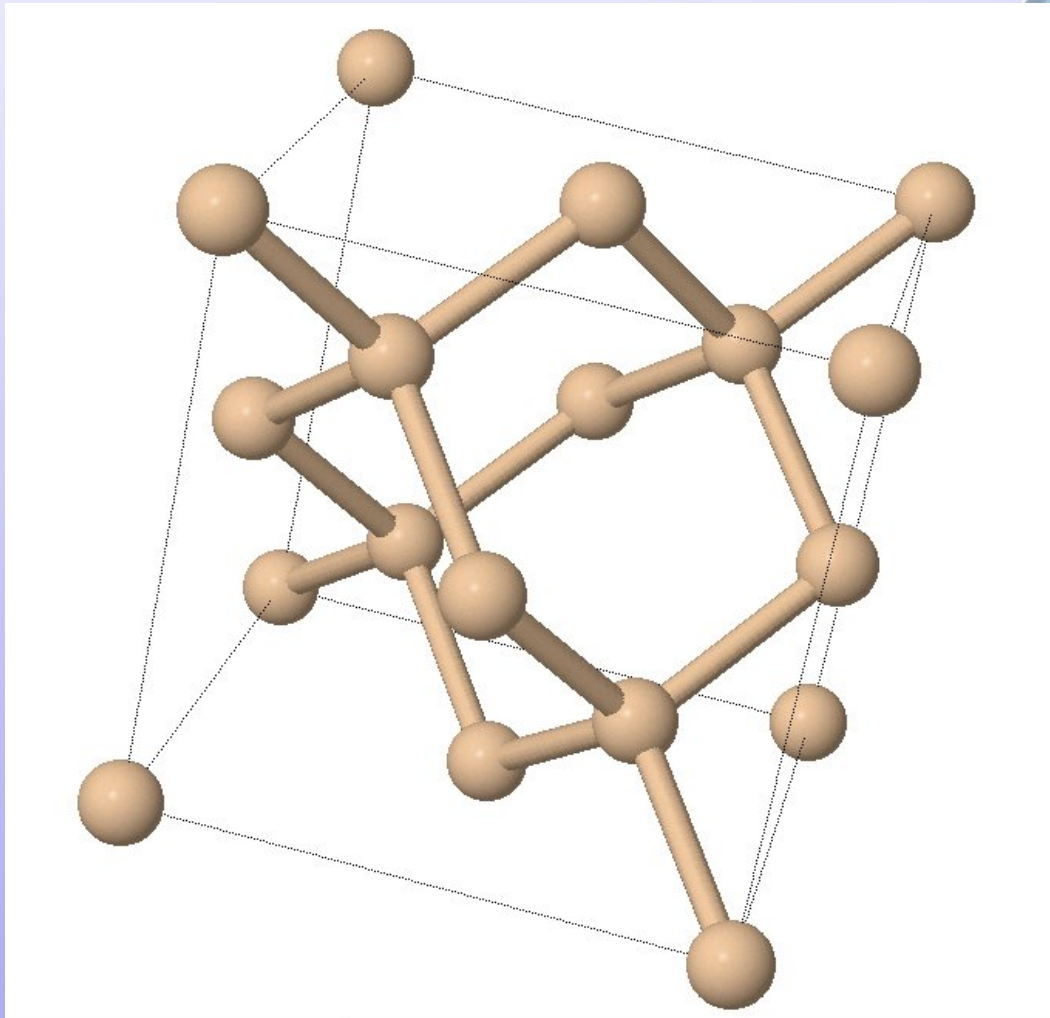
the crystallographic planes are identified with three *integer* numbers $\langle hkl \rangle$

The plane is normal to the vector:

$$\vec{v} = (h, k, l)$$



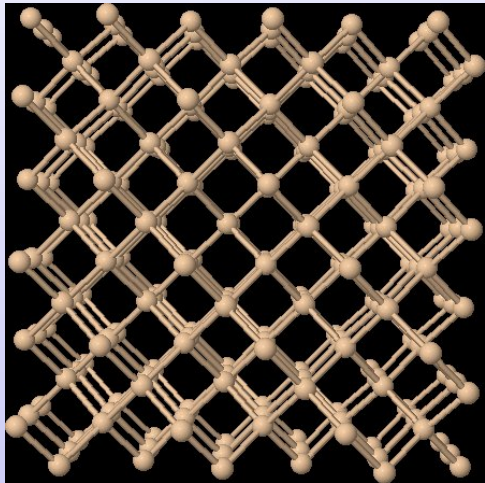
Face Centered Cubic (FCC) crystal



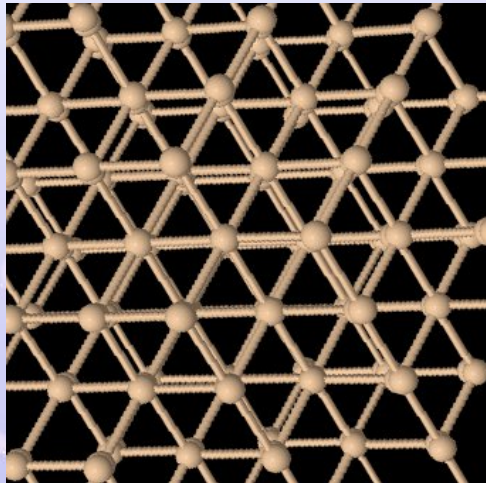
let's look at the
silicon crystal
structure:

By rotating the silicon crystal in space, various configurations are accessible:

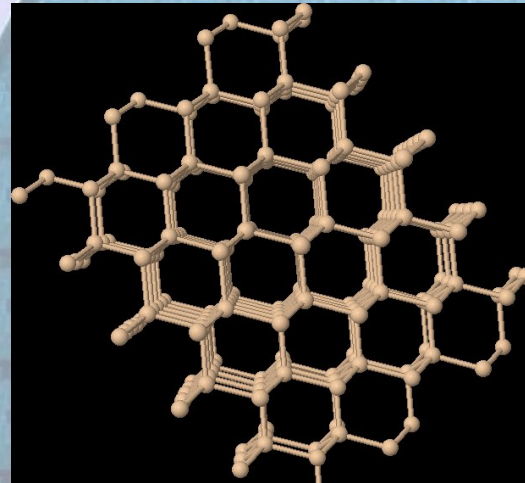
.... some with a clear “structure”



$\langle 100 \rangle$

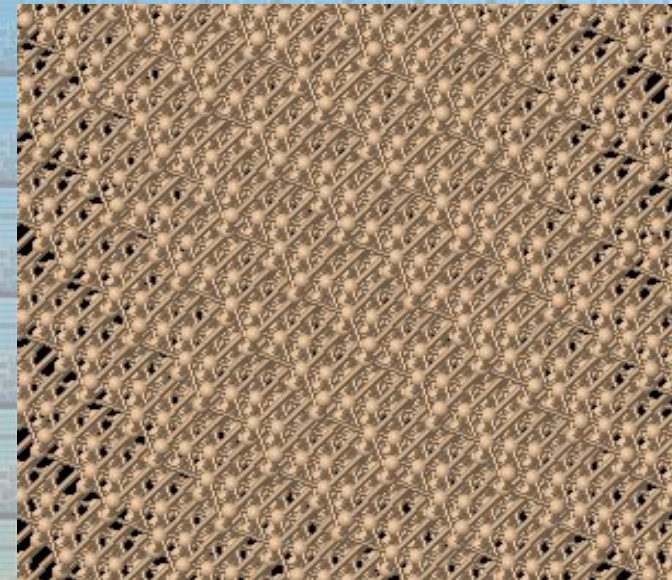


$\langle 111 \rangle$



$\langle 110 \rangle$

... but also some with a nearly-amorphous or “random” structure.

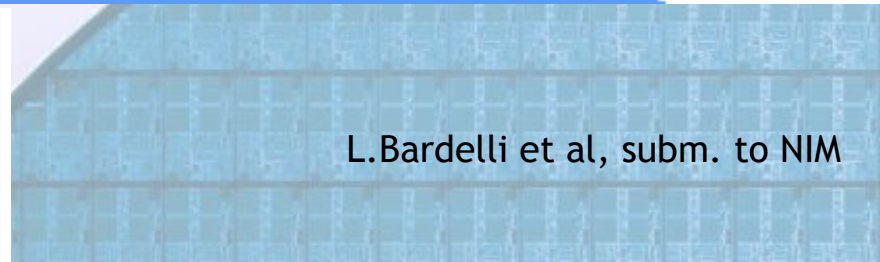
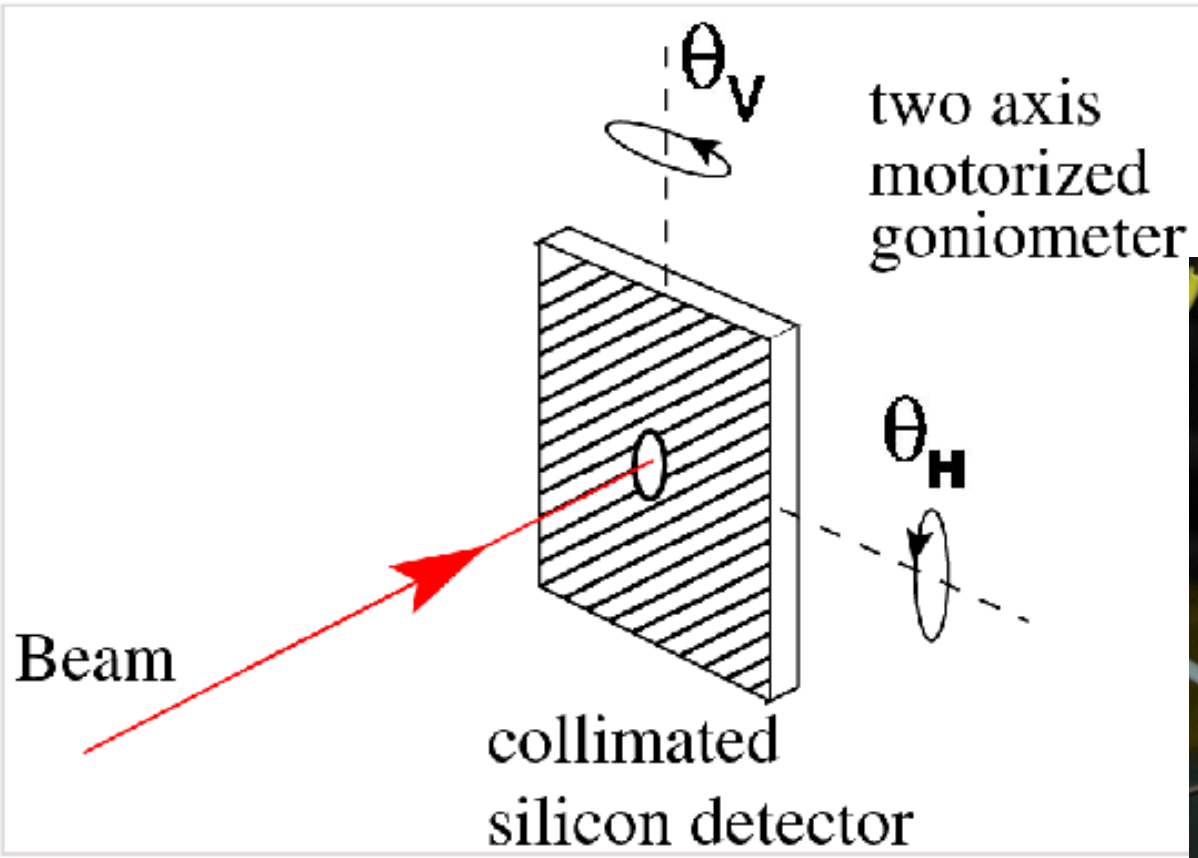


The FAZIA collaboration has performed *two* experimental campaigns in order to study the influence of channeling effects in silicon for pulse-shape applications

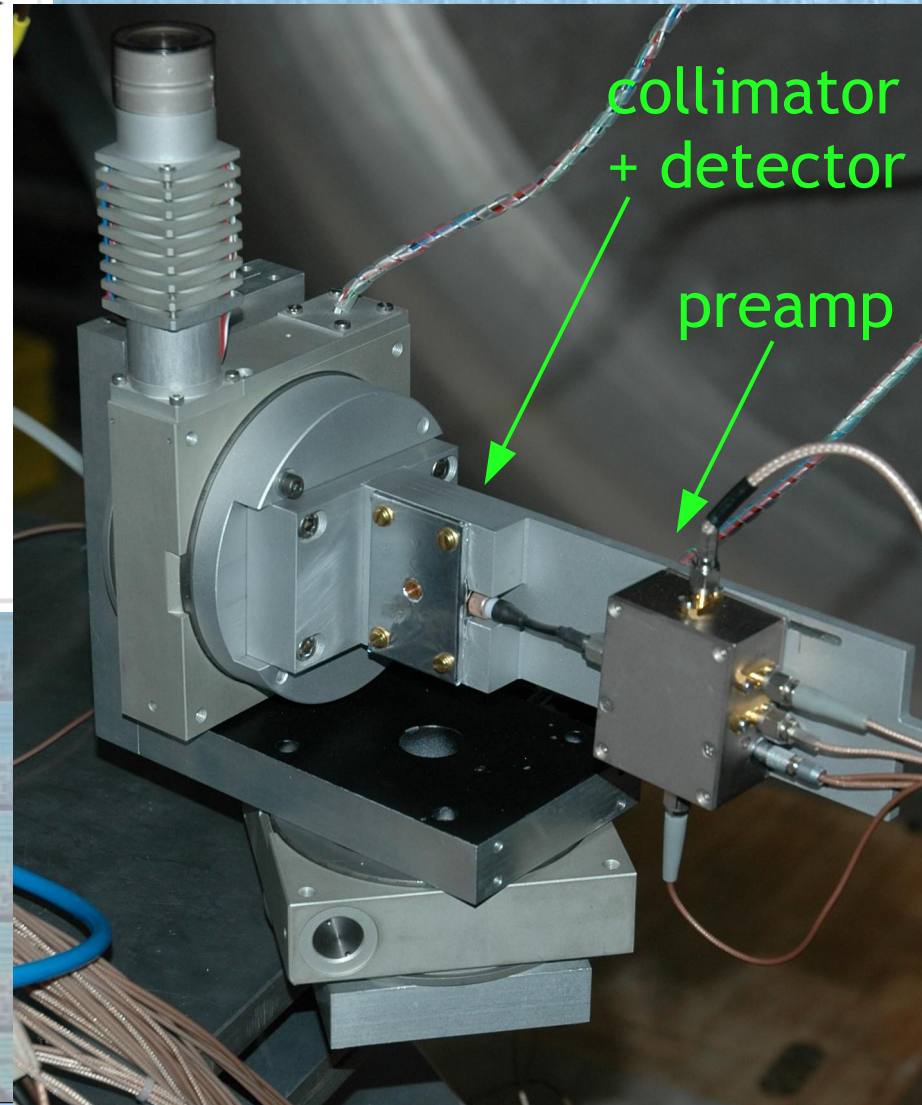
Experimental goals:

- 1) which is the importance of channeling effects?
are they able to spoil the experimental “resolution” ?
- 2) if yes, is it possible to avoid these effects? how?

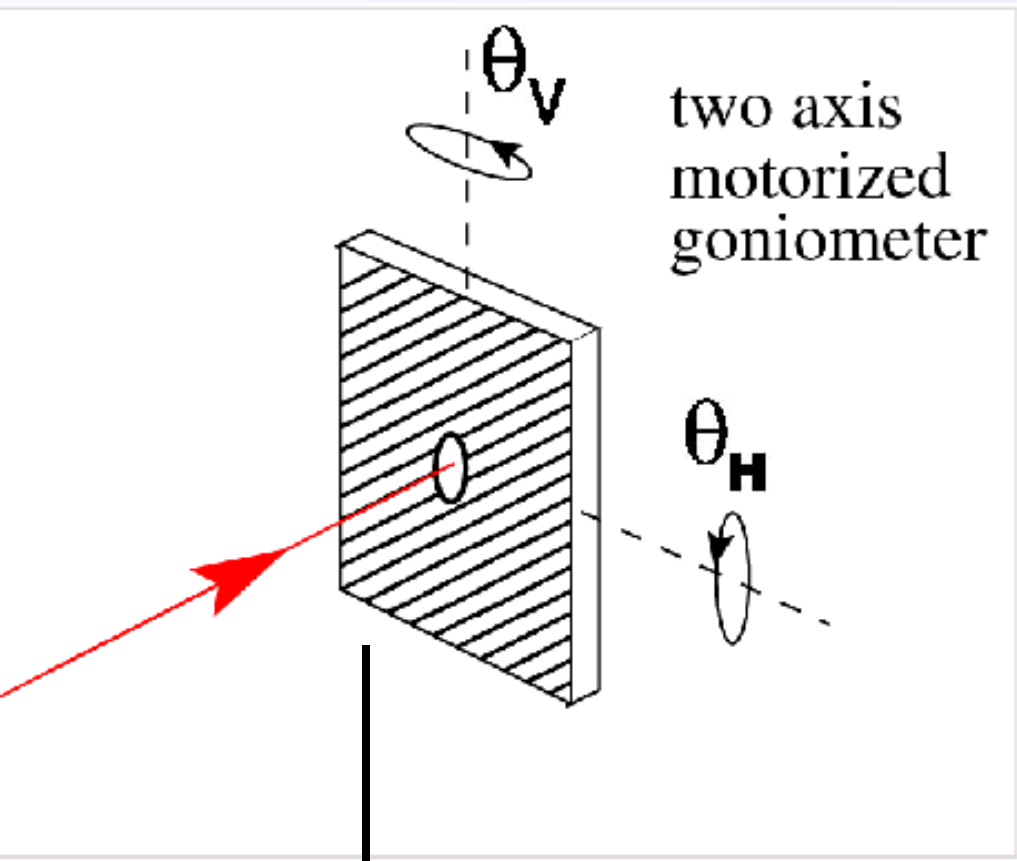
L.Bardelli et al, subm. to NIM



L. Bardelli et al, subm. to NIM



Measure the detector response at various tilt angles by using a motorized support (with remote control)



Tested ions:

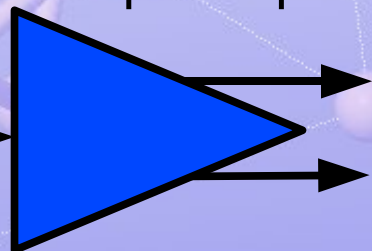
$^{80}, ^{82}\text{Se}$ @ 410 MeV

$^{58}, ^{60}\text{Ni}$ @ 703 MeV

^{32}S @ 160 MeV

all tests performed at
LNL

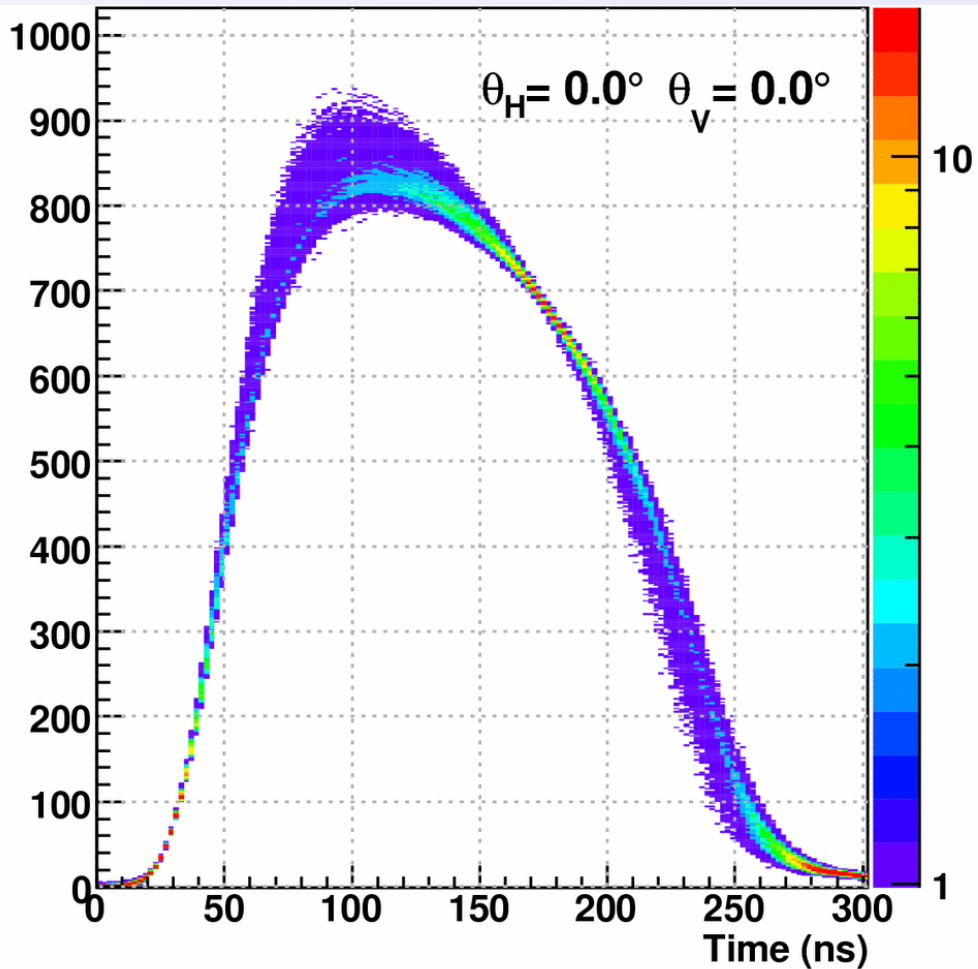
PACI charge and
current preamplifier



INFN-Fi digitizer: G.Pasquali et al, NIM A 570 (2007)

Fast sampling ADCs
12 bit, 125 MS/s
(9 bit, 2 GS/s tested also)

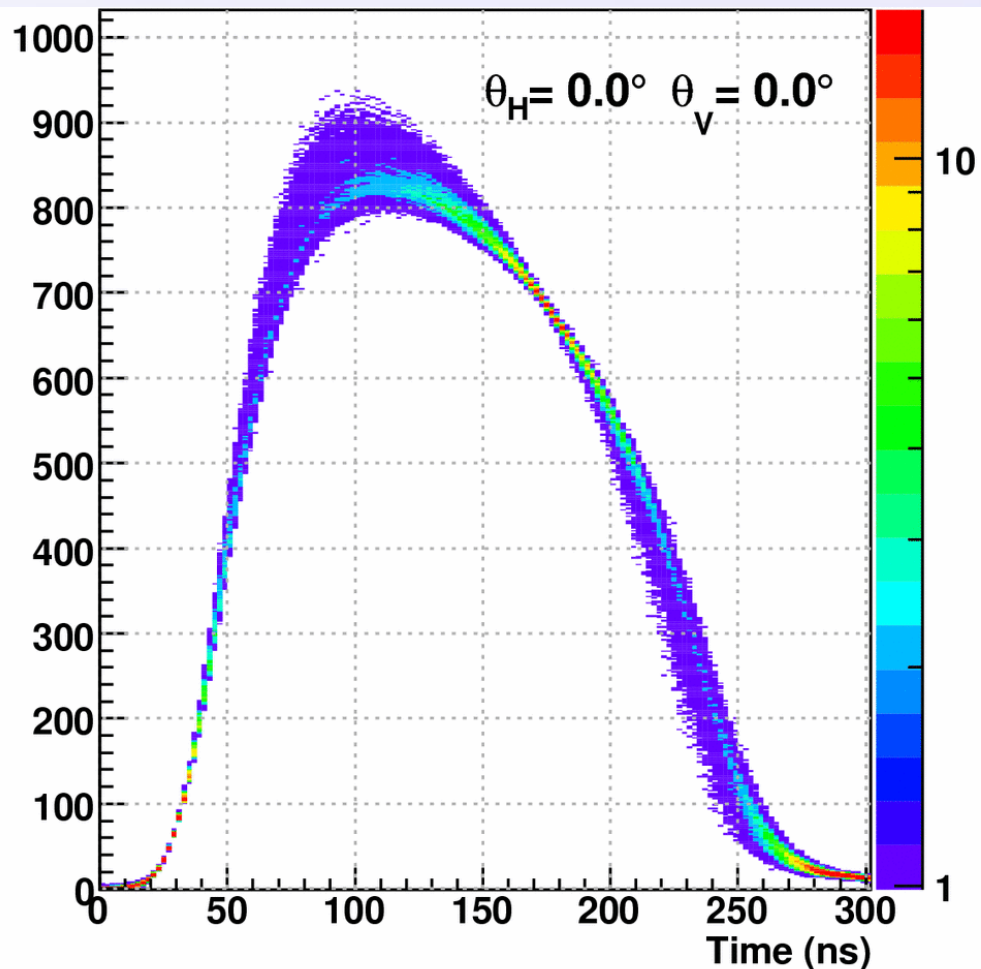
Current signals for a ^{80}Se @ 410MeV, $\langle 100 \rangle$ detector, 1000 events:



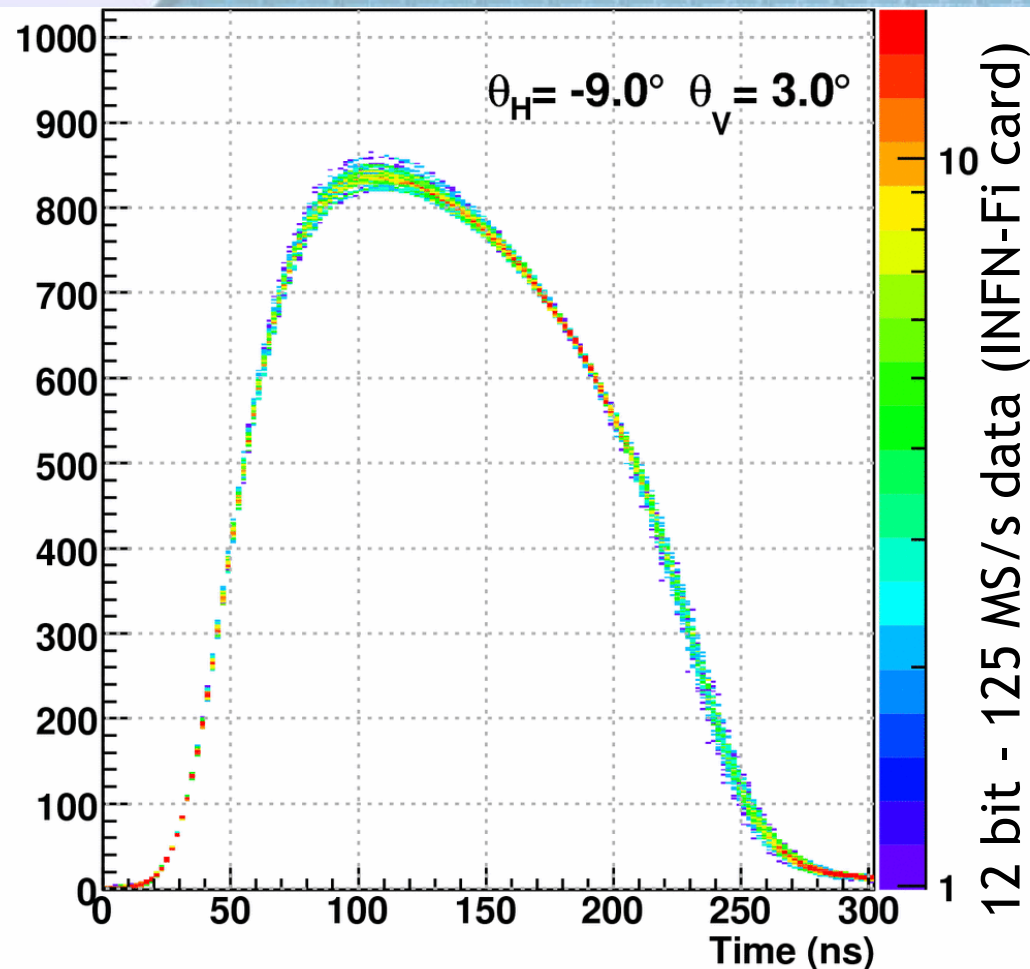
12 bit - 125 MS/s data (INFN-Fi card)

standard detector mounting
(normal to direction of incoming particles)

Current signals for a ^{80}Se @ 410MeV, $\langle 100 \rangle$ detector, 1000 events:



standard detector mounting
(normal to direction of incoming particles)



tilted detector
**impressive improvement in
signal dispersion!**

For each event:

- the particle energy is extracted via optimized digital shaping
- the signal risetime (either charge or current) is extracted via a digital CFD algorithm with proper interpolation
[for details see L.Bardelli et al, NIM A 521 (2004)]

For each explored angle pair we can plot:

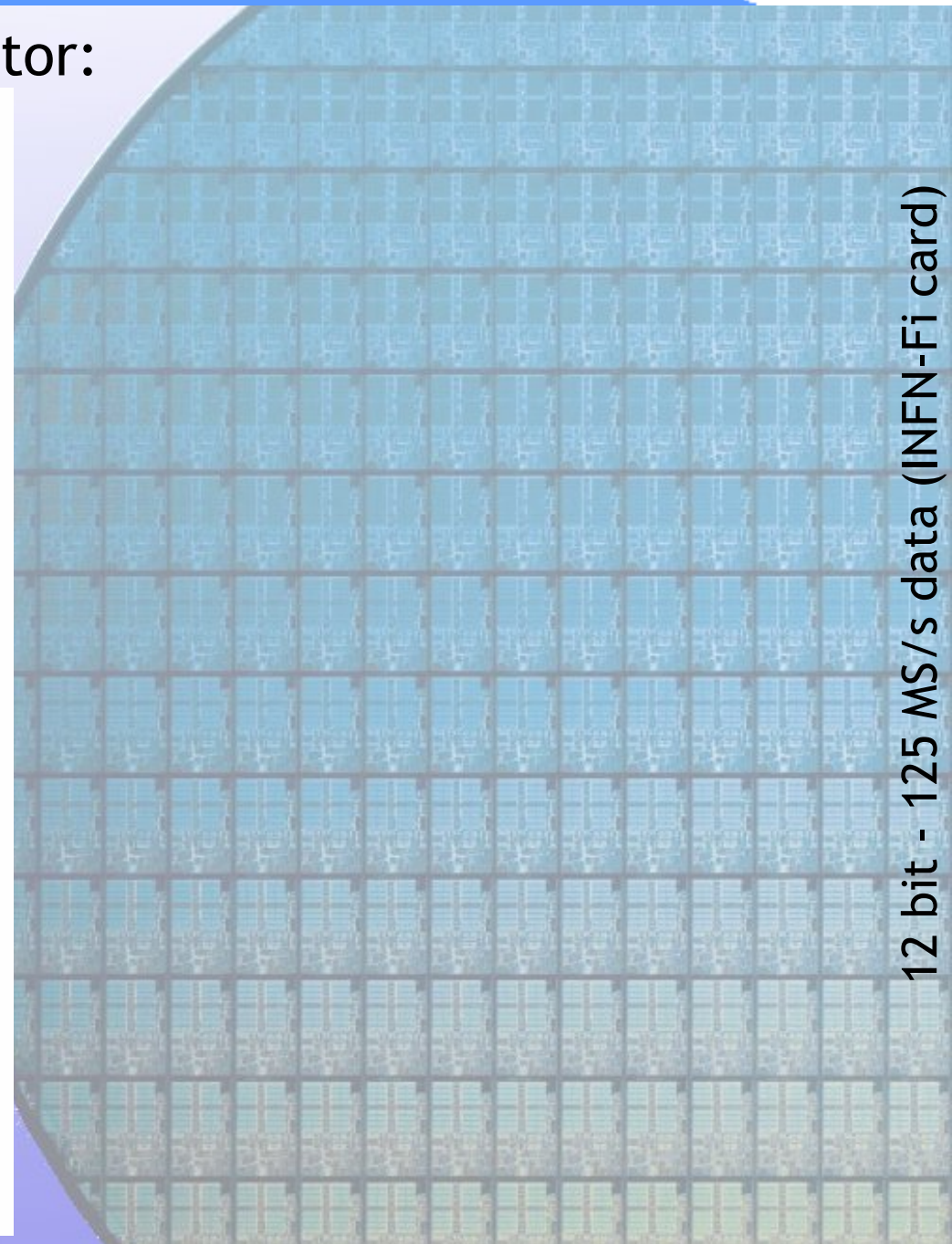
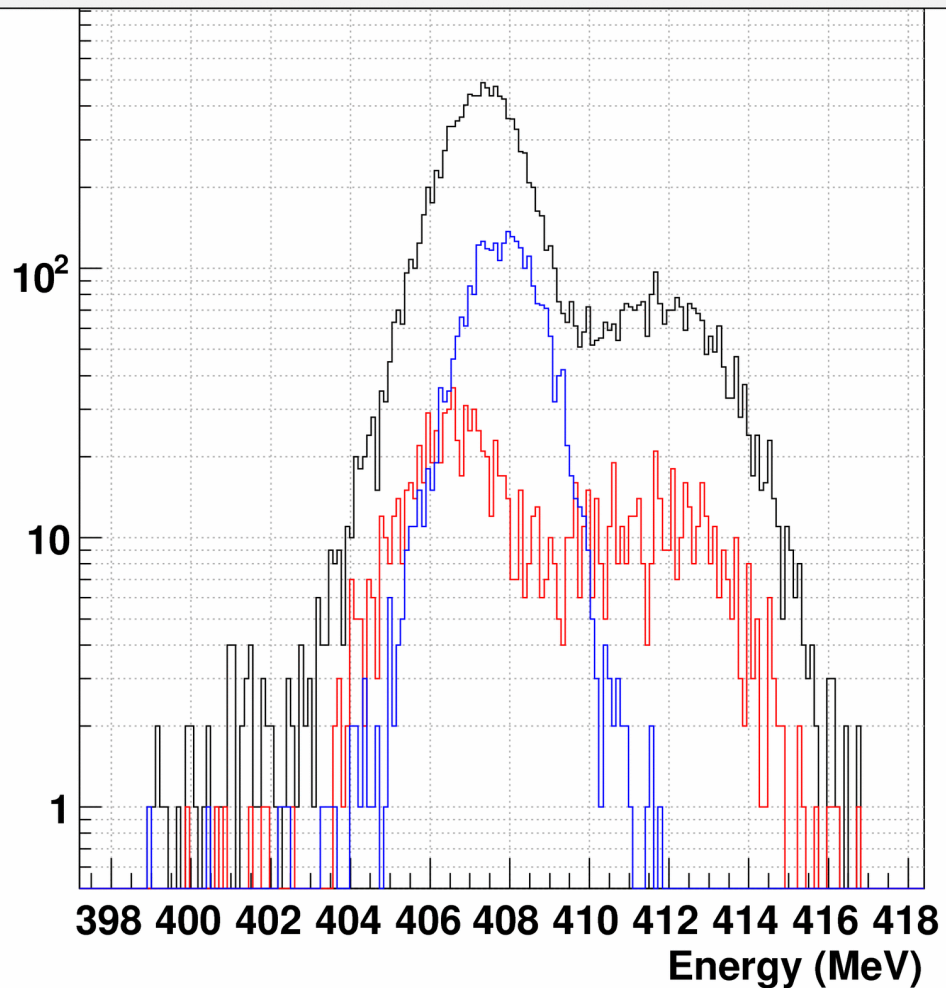
- energy resolution as a function of the two angles
- risetime resolution as a function of the two angles
- etc etc...

Let's see some examples.....

Energy resolution for a $\langle 111 \rangle$ detector:

Beam: ^{82}Se @ 408 MeV - $\langle 111 \rangle$ det.

- Full detector ($\pm 4^\circ$): RMS=2.21 MeV
- Channeled direction (0,0): RMS=2.87 MeV
- Random area: RMS=1.02 MeV

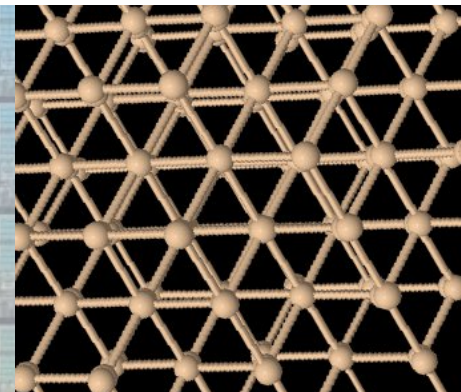
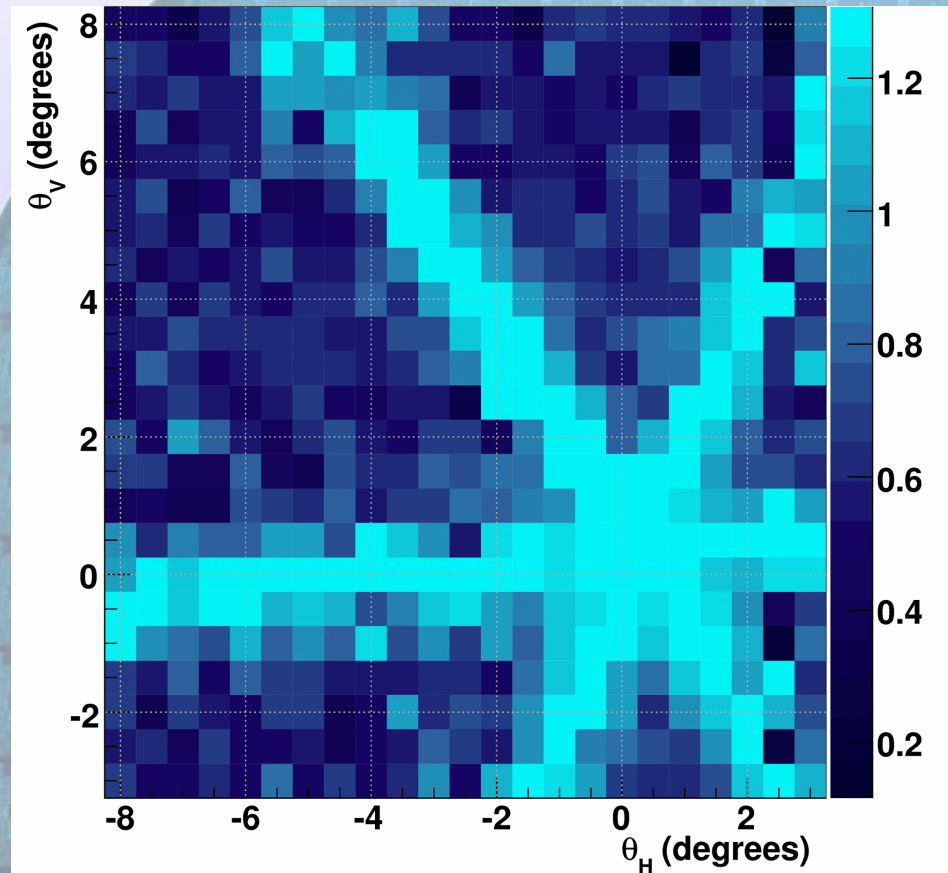
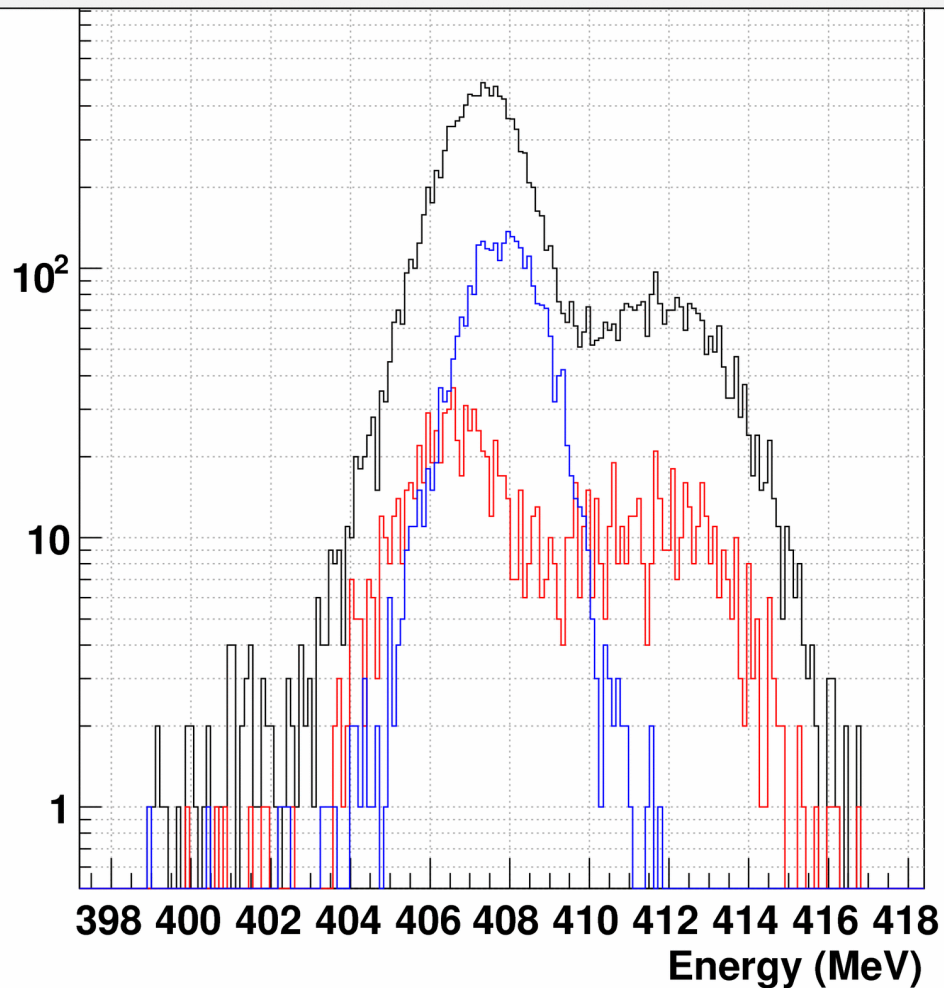


12 bit - 125 MS/s data (INFN-Fi card)

Energy resolution for a $\langle 111 \rangle$ detector:

Beam: ^{82}Se @ 408 MeV - $\langle 111 \rangle$ det.

- Full detector ($\pm 4^\circ$): RMS=2.21 MeV
- Channeled direction (0,0): RMS=2.87 MeV
- Random area: RMS=1.02 MeV



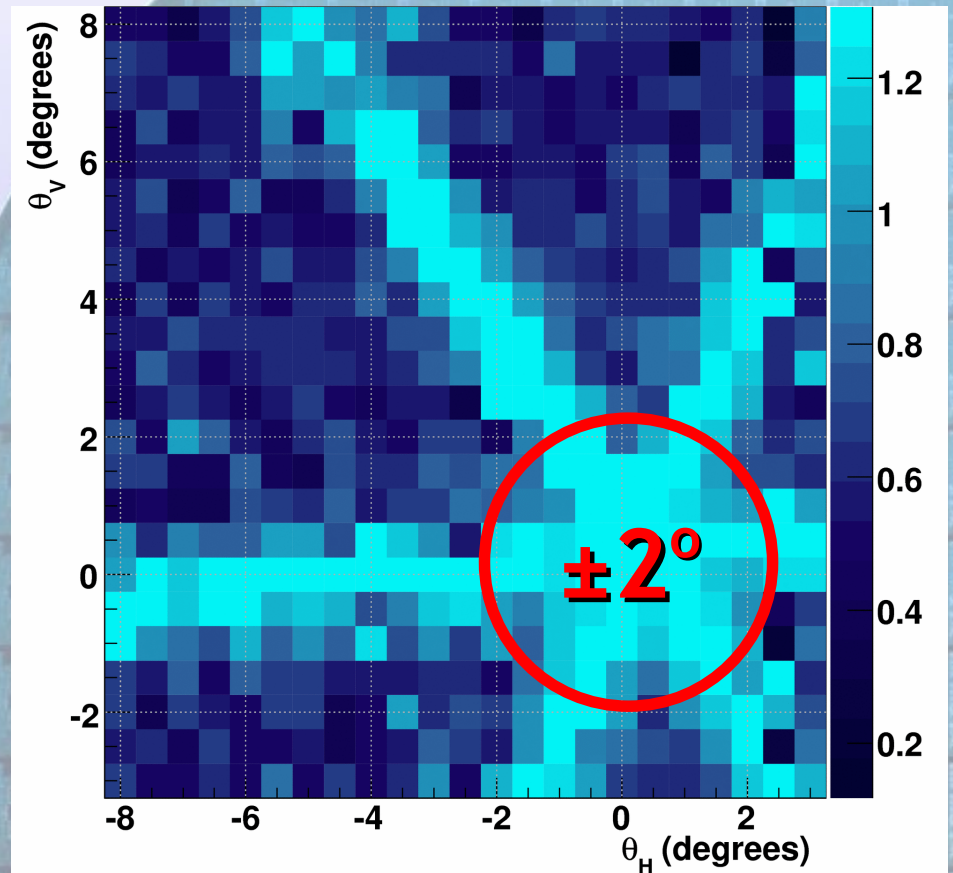
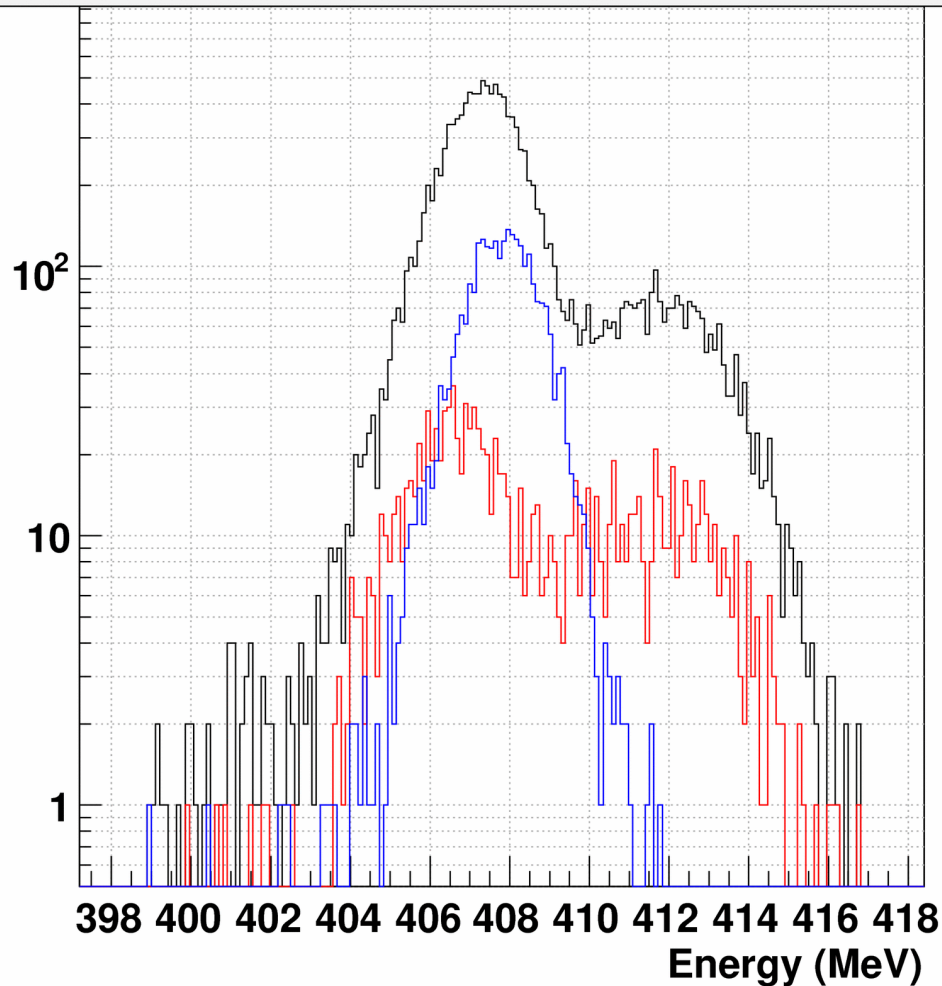
detector structure

12 bit - 125 MS/s data (INFN-Fi card)

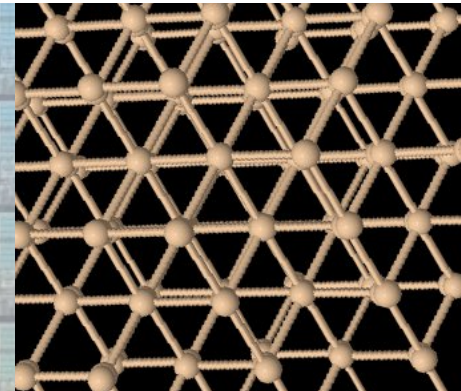
Energy resolution for a $\langle 111 \rangle$ detector:

Beam: ^{82}Se @ 408 MeV - $\langle 111 \rangle$ det.

- Full detector ($\pm 4^\circ$): RMS=2.21 MeV
- Channeled direction (0,0): RMS=2.87 MeV
- Random area: RMS=1.02 MeV



12 bit - 125 MS/s data (INFN-Fi card)

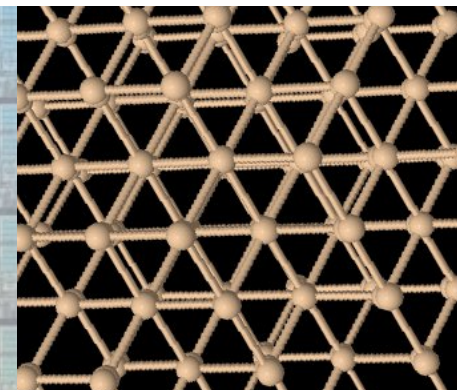
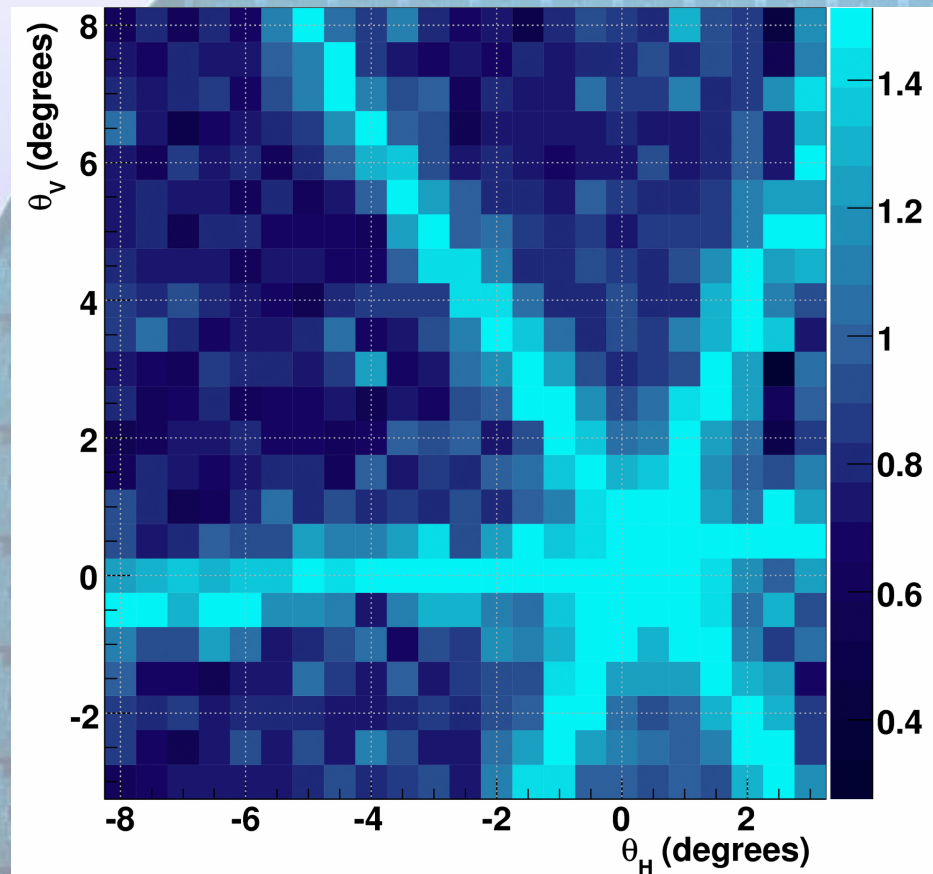
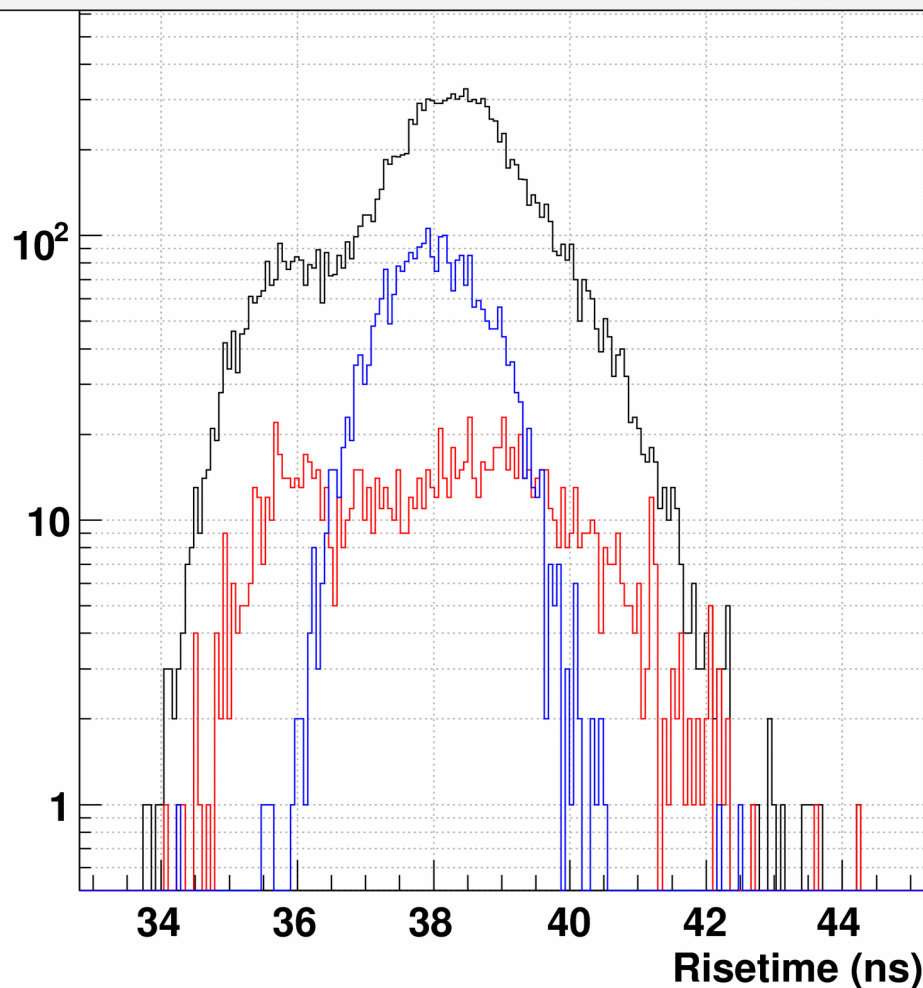


detector structure

Risetime resolution for a $\langle 111 \rangle$ detector:

Beam: ^{82}Se @ 408 MeV - $\langle 111 \rangle$ det.

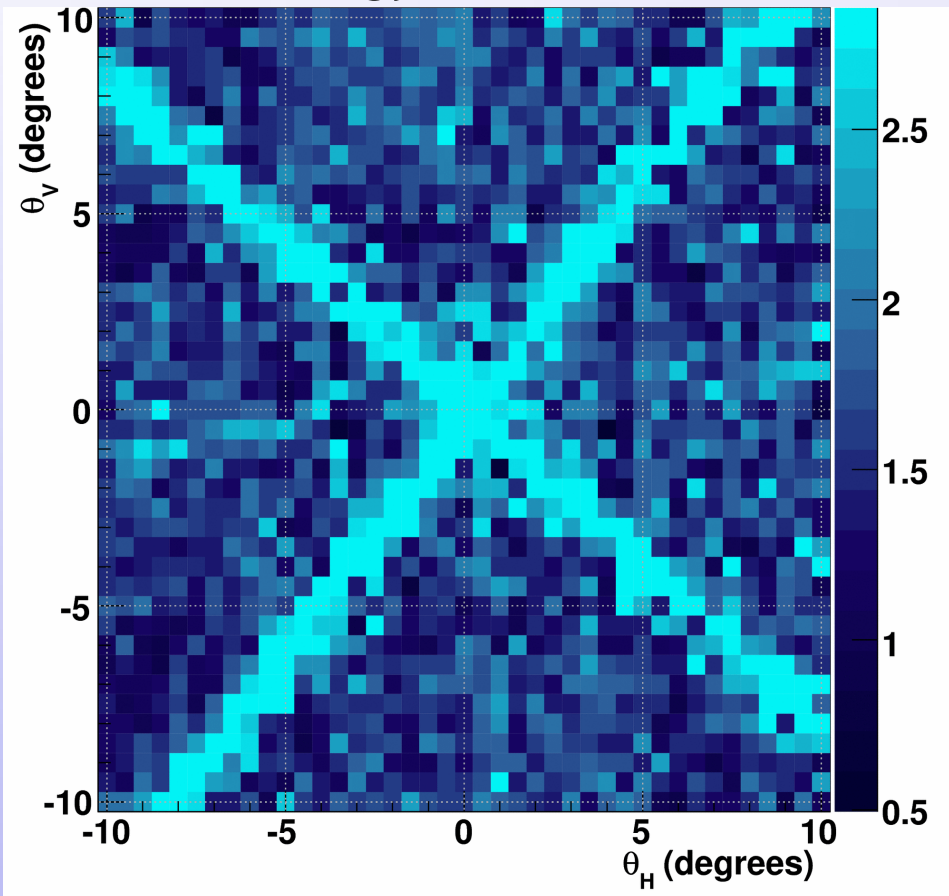
- Full detector ($\pm 4^\circ$): RMS=1.36 ns
- Channeled direction (0,0): RMS=1.78 ns
- Random area: RMS=0.76 ns



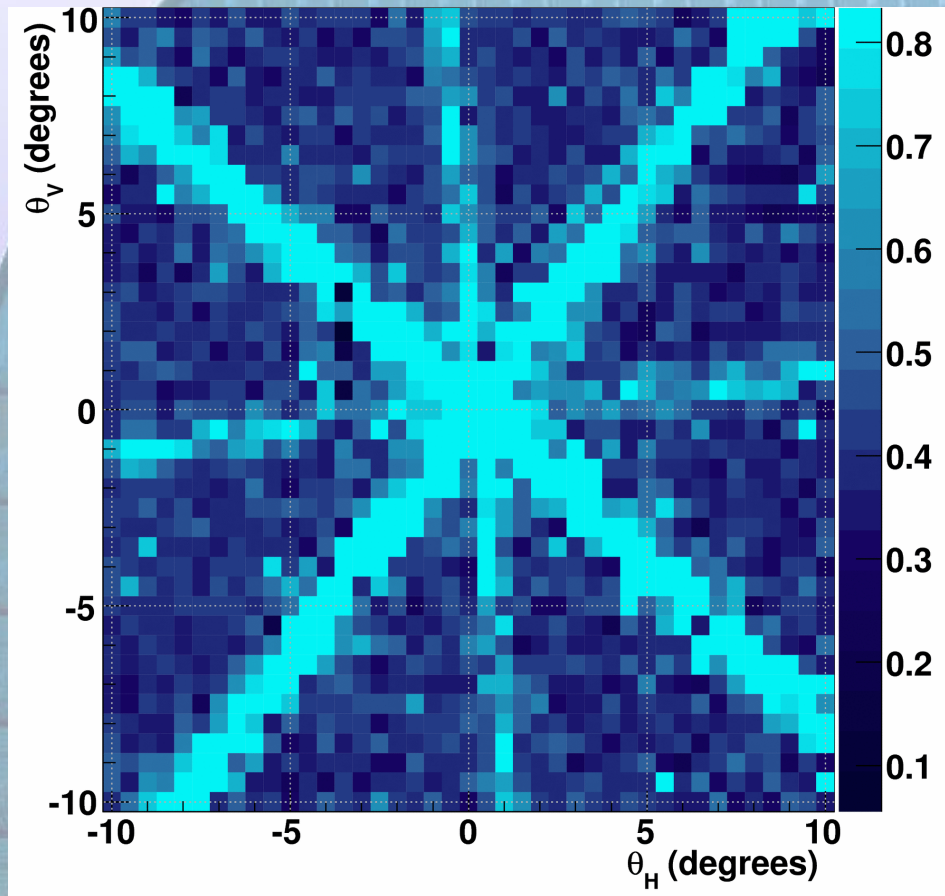
detector structure

12 bit - 125 MS/s data (INFN-Fi card)

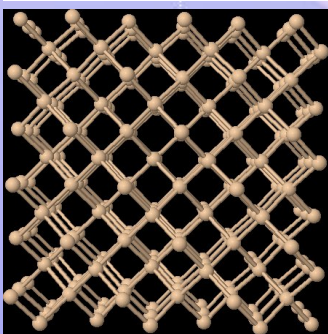
Same behaviour:
energy resolution



risetime resolution



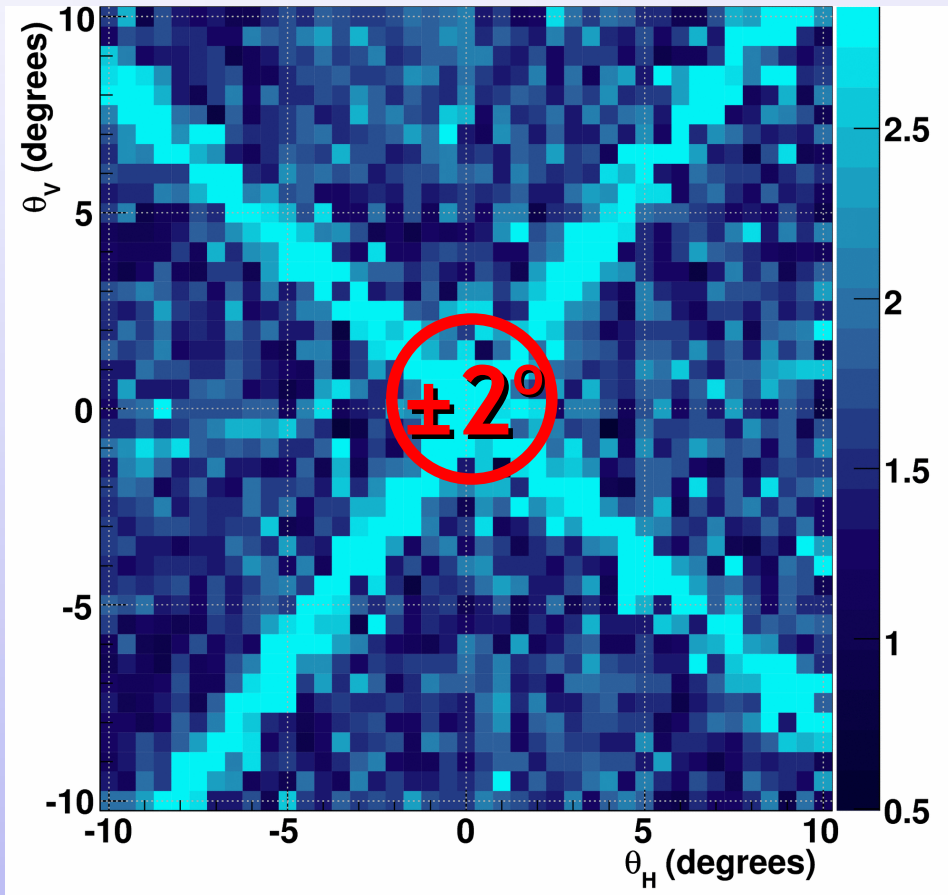
12 bit - 125 MS/s data (INFN-Fi card)



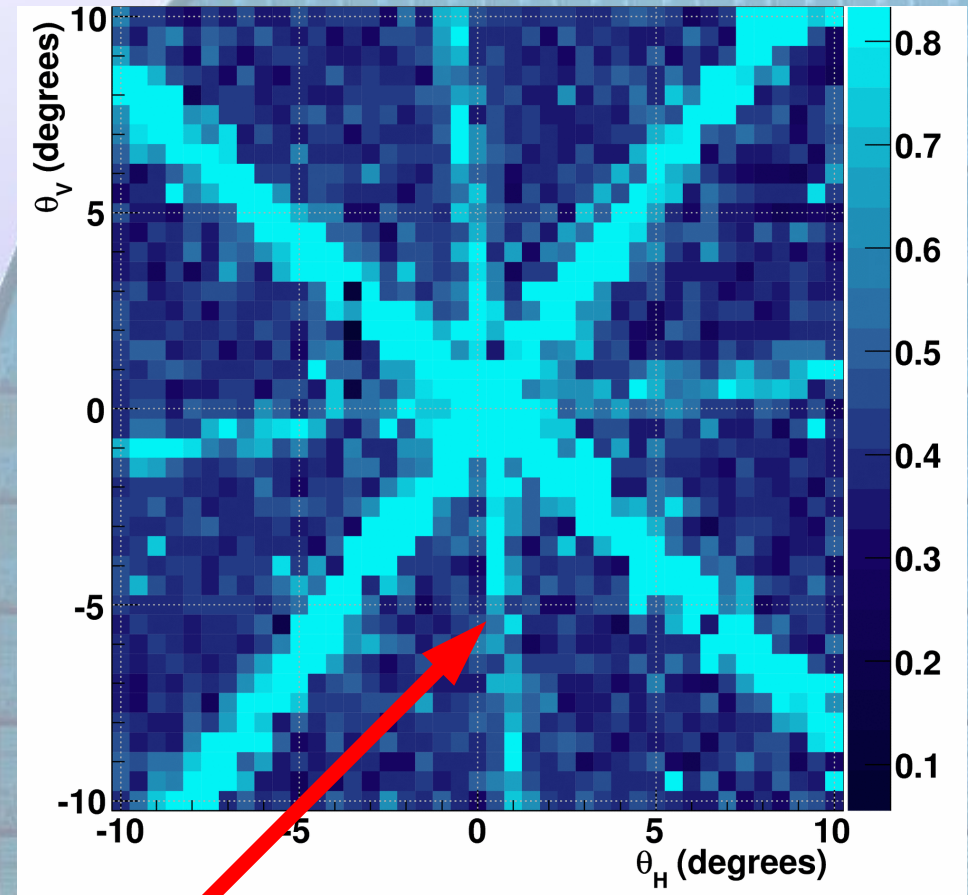
detector structure

L. Bardelli et al, subm. to NIM

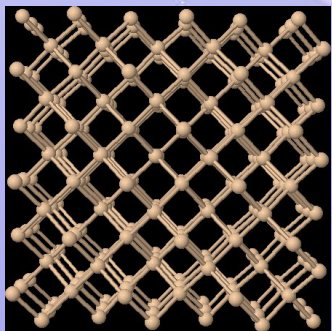
energy resolution



risetime resolution



12 bit - 125 MS/s data (INFN-Fi card)

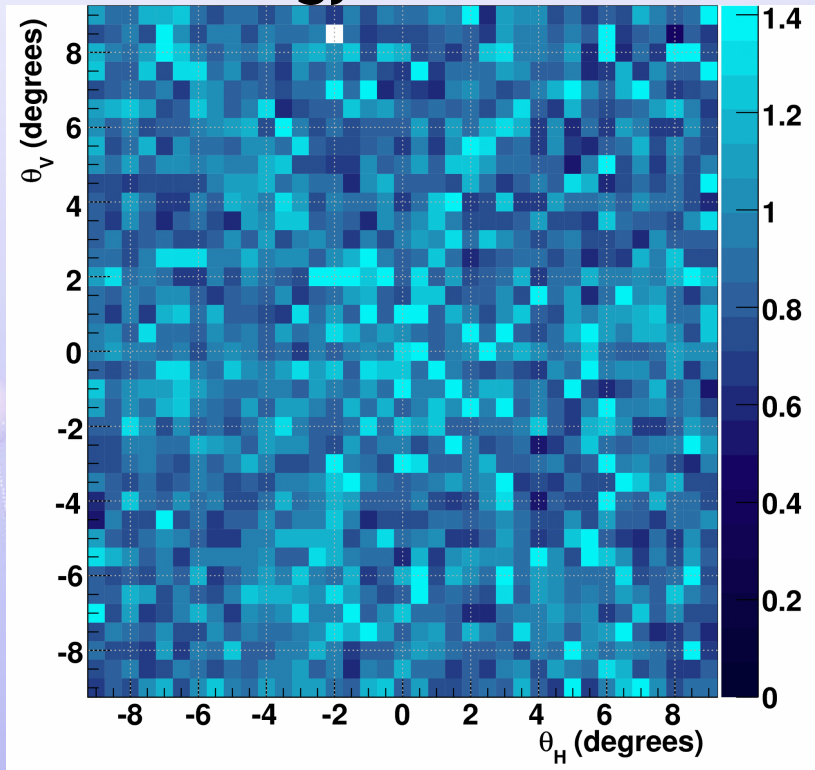


detector structure

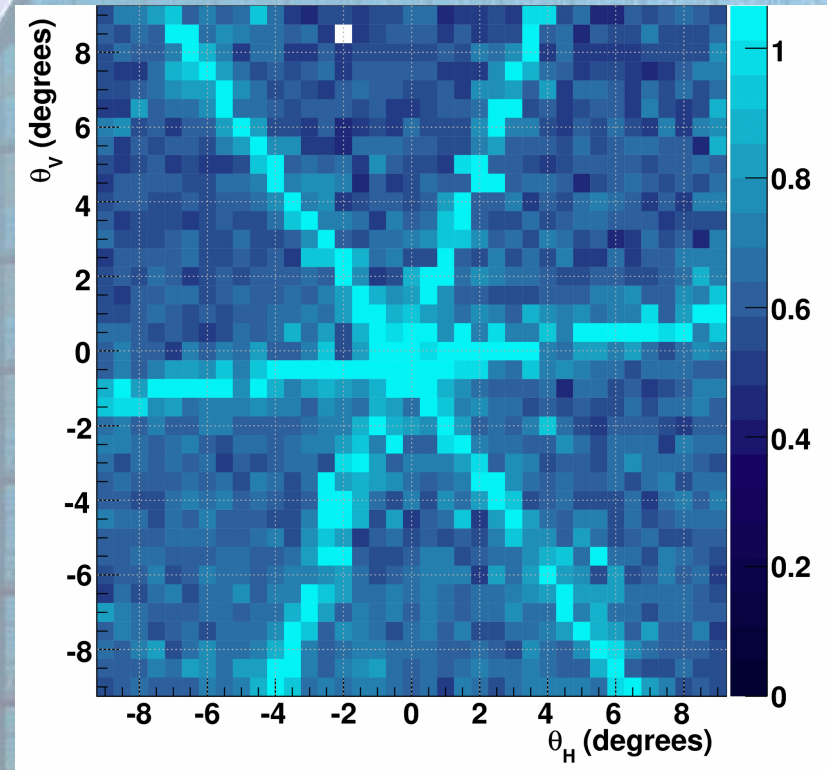
risetime can appreciate also higher order crystallographic planes

Experimental data for ^{32}S ions @ 5 AMeV (<111> detector):

energy resolution

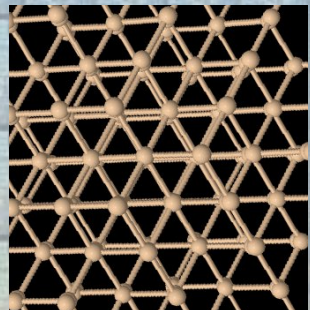


risetime resolution



12 bit - 125 MS/s data (INFN-Fi card)

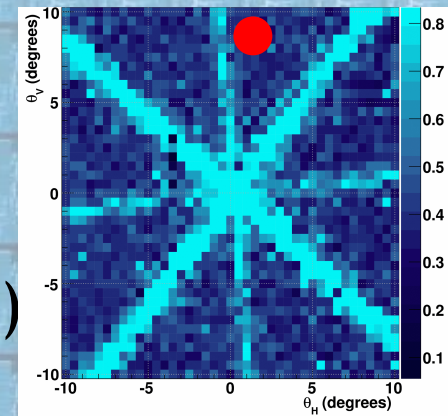
For these “light” ions where the pulse height defect is small, the energy resolution is not affected by channeling, while the pulse shape is.



We have demonstrated that channeling effects must be avoided in order to obtain good performances in PSA applications.

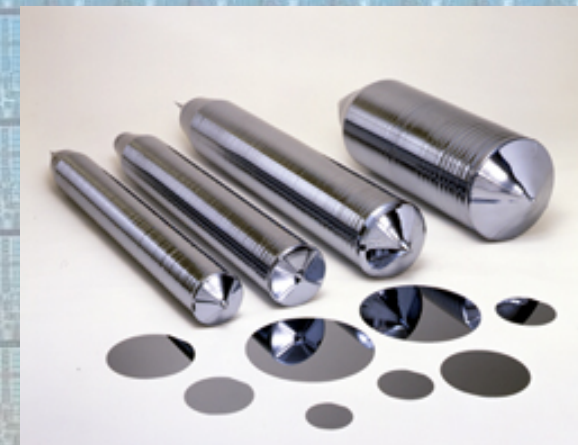
How can we avoid these effects??

1) if the detector is cut along a $\langle 111 \rangle$ or $\langle 100 \rangle$ axis, the only solution is to tilt it (not ok for 4π device...)



2) we can ask manufactures to build detectors from silicon wafers having a special cut

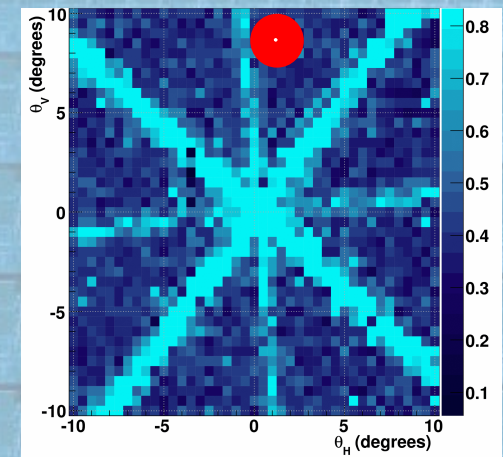
FAZIA is already working in this direction (first detectors in progress)



In both cases the angle covered by the detector must be small (rule of thumb: $< \pm 2^\circ$)

Silicon wafers can be cut from silicon ingots with a special cut: in order to recover the “best” experimental configuration, two angles are needed: for $\langle 100 \rangle$ $\theta_{\text{off}} = 8^\circ$, $\varphi = 13^\circ$

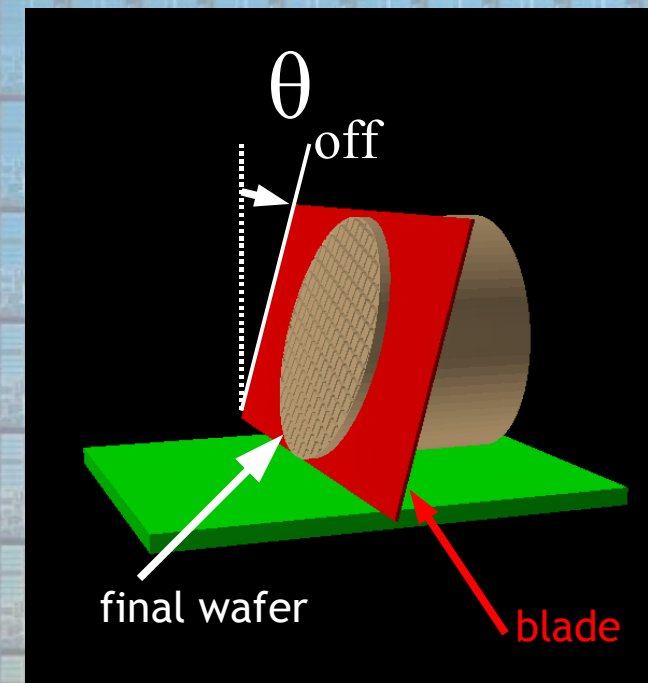
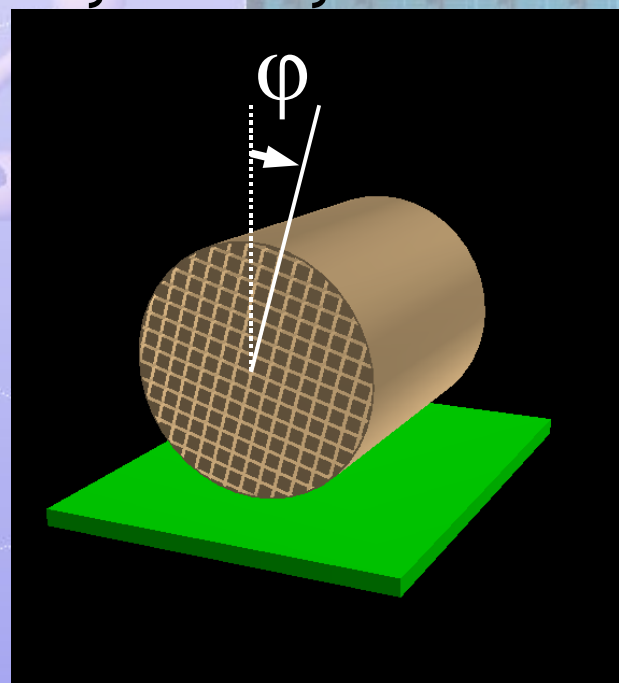
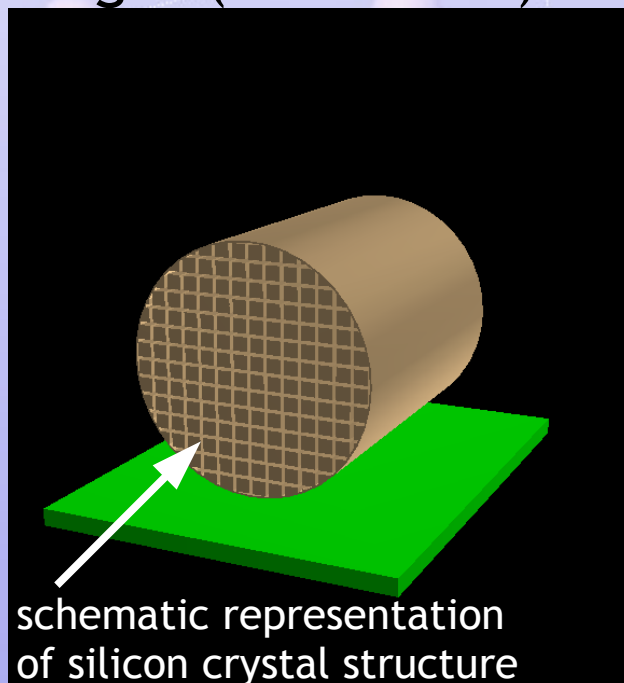
Maximum angular detector coverage: $\pm 2^\circ$



start from a silicon ingot (i.e. $\langle 100 \rangle$)...

...rotate along the symmetry axis...

...perform an off-axis wafer cut.

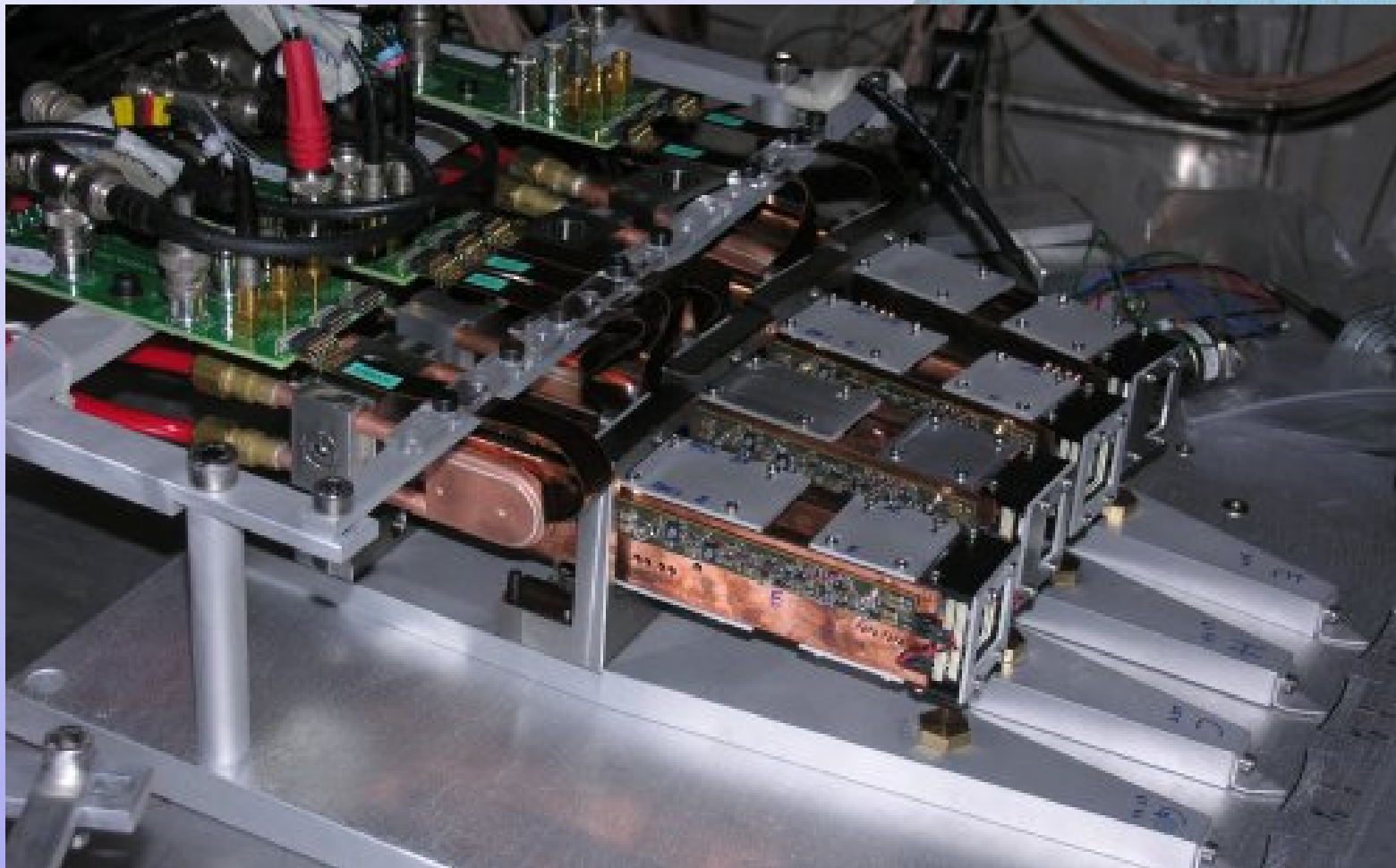




EXPERIMENTS



In December 2008, the FAZIA collaboration has performed an experimental test in LNL, in order to test the performances of our detectors and basic idea of our frontend:



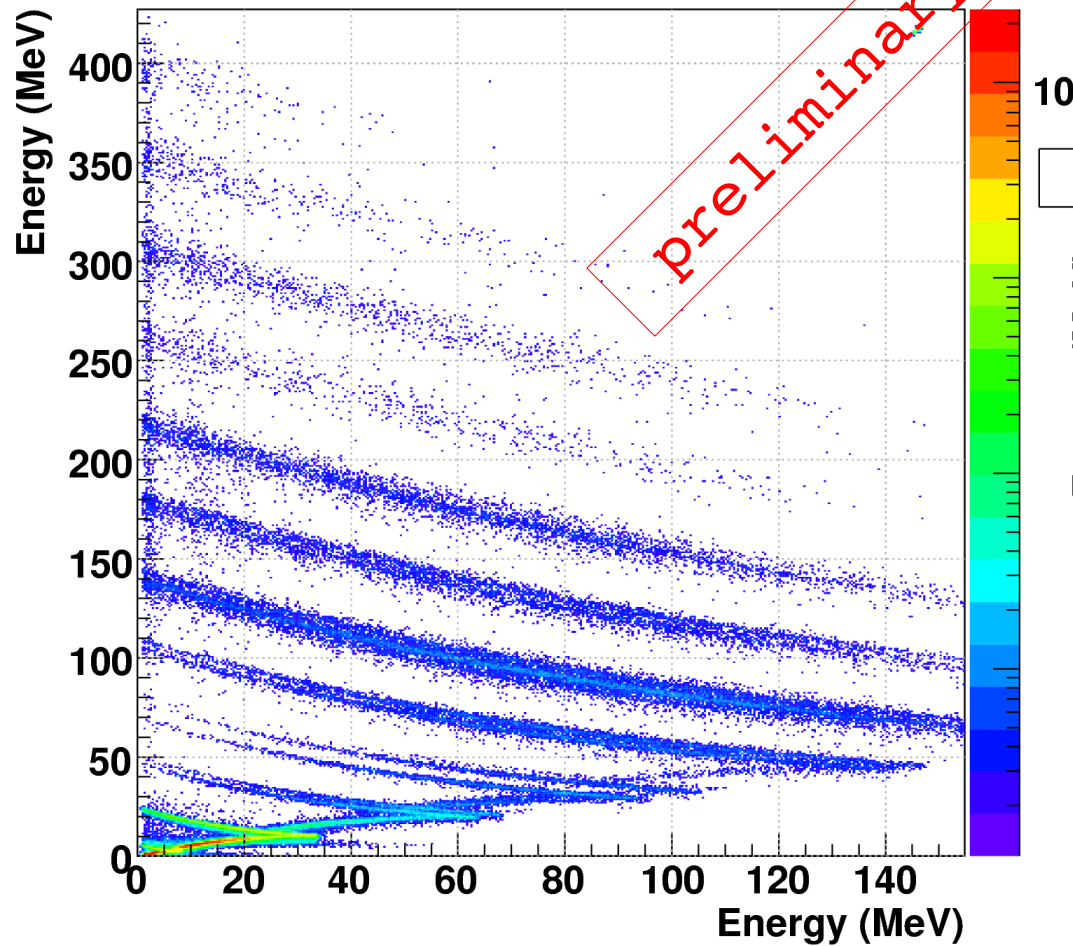
Several Si-Si or
Si-CsI
telescopes in
various
configurations
and different
readouts...

Channeling effects in $\Delta E-E$



“with” channeling

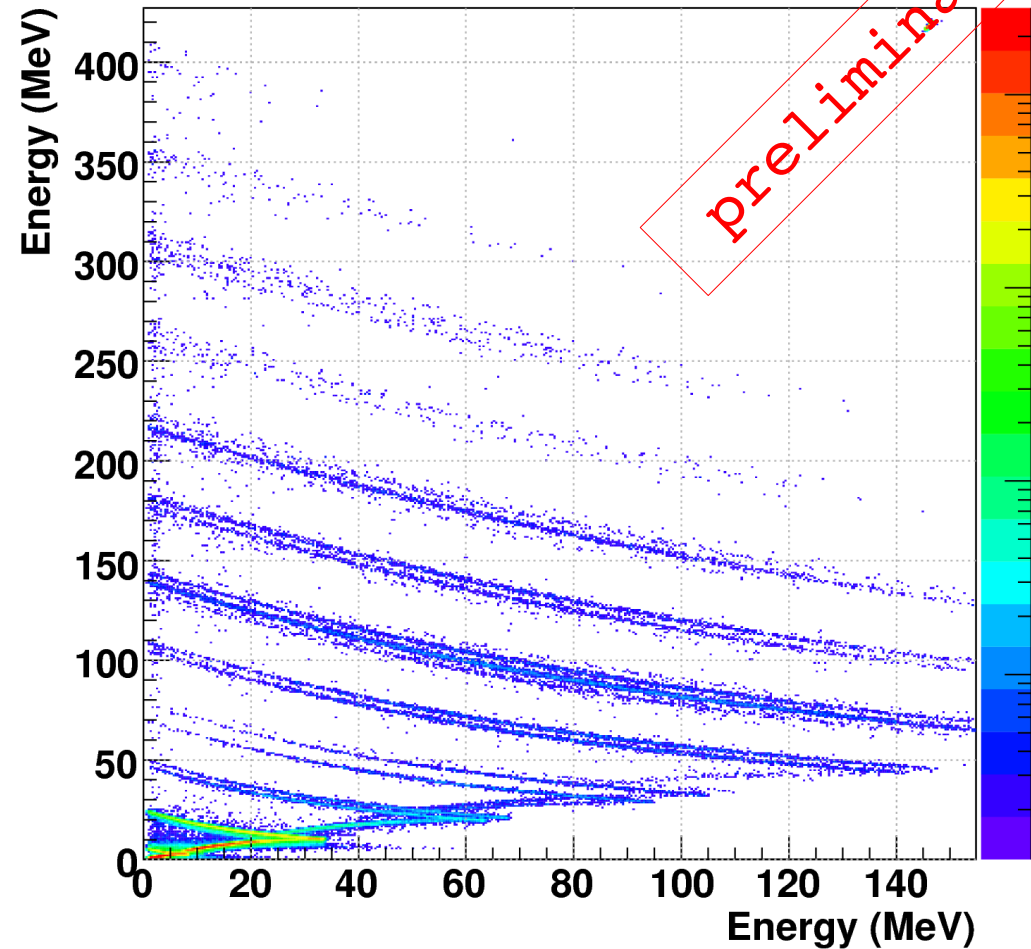
$\Delta E-E$ (tele.G) - channeled configuration



14bit, 100 MS/s digitizer
4.2 GeV full range in ΔE

“without” channeling

$\Delta E-E$ (tele.G) - random configuration

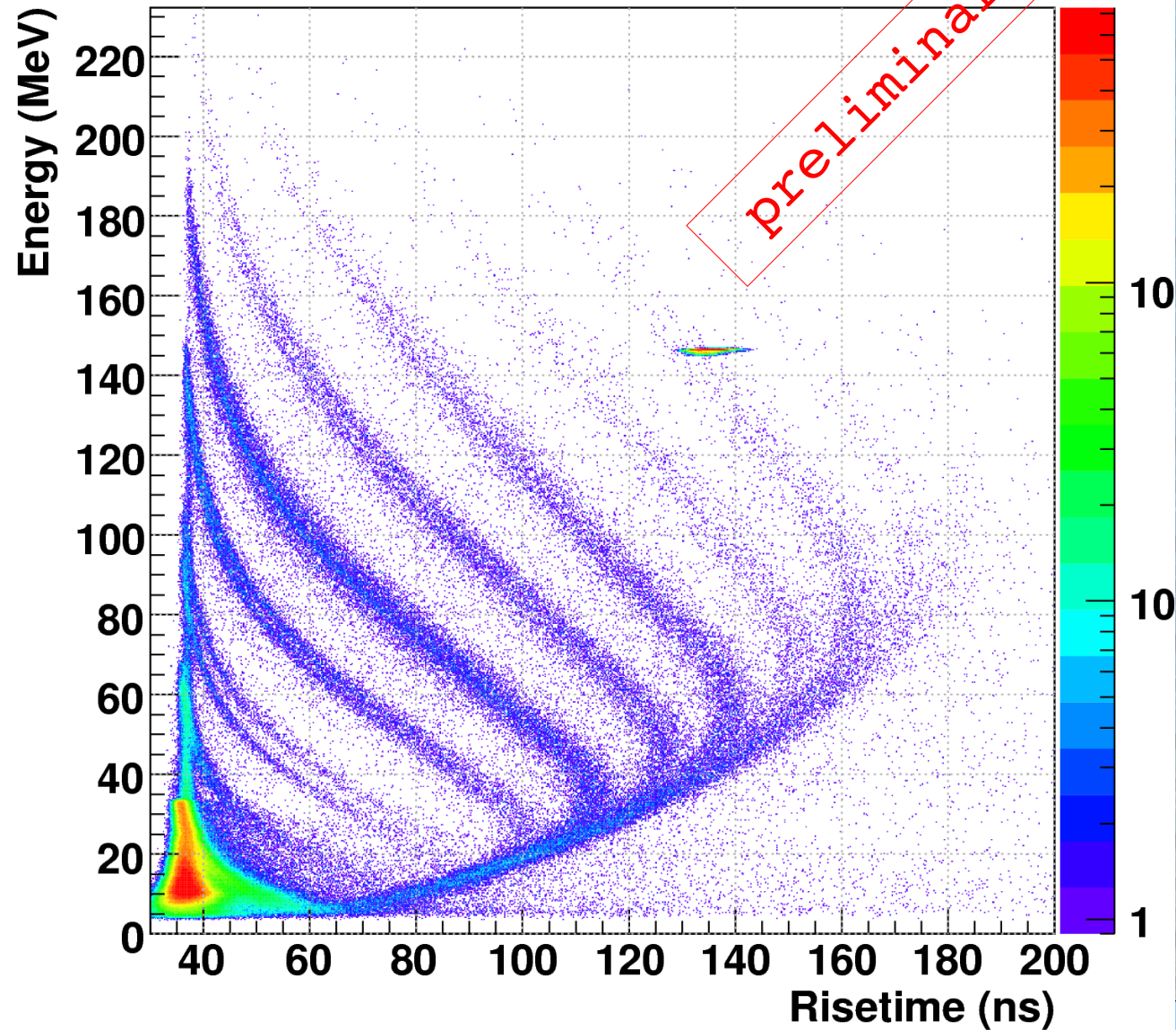


500 um detector
1.5% non-hom. (BEST)

“with” channeling



Energy vs risetime (det.G-E) - channeled configuration



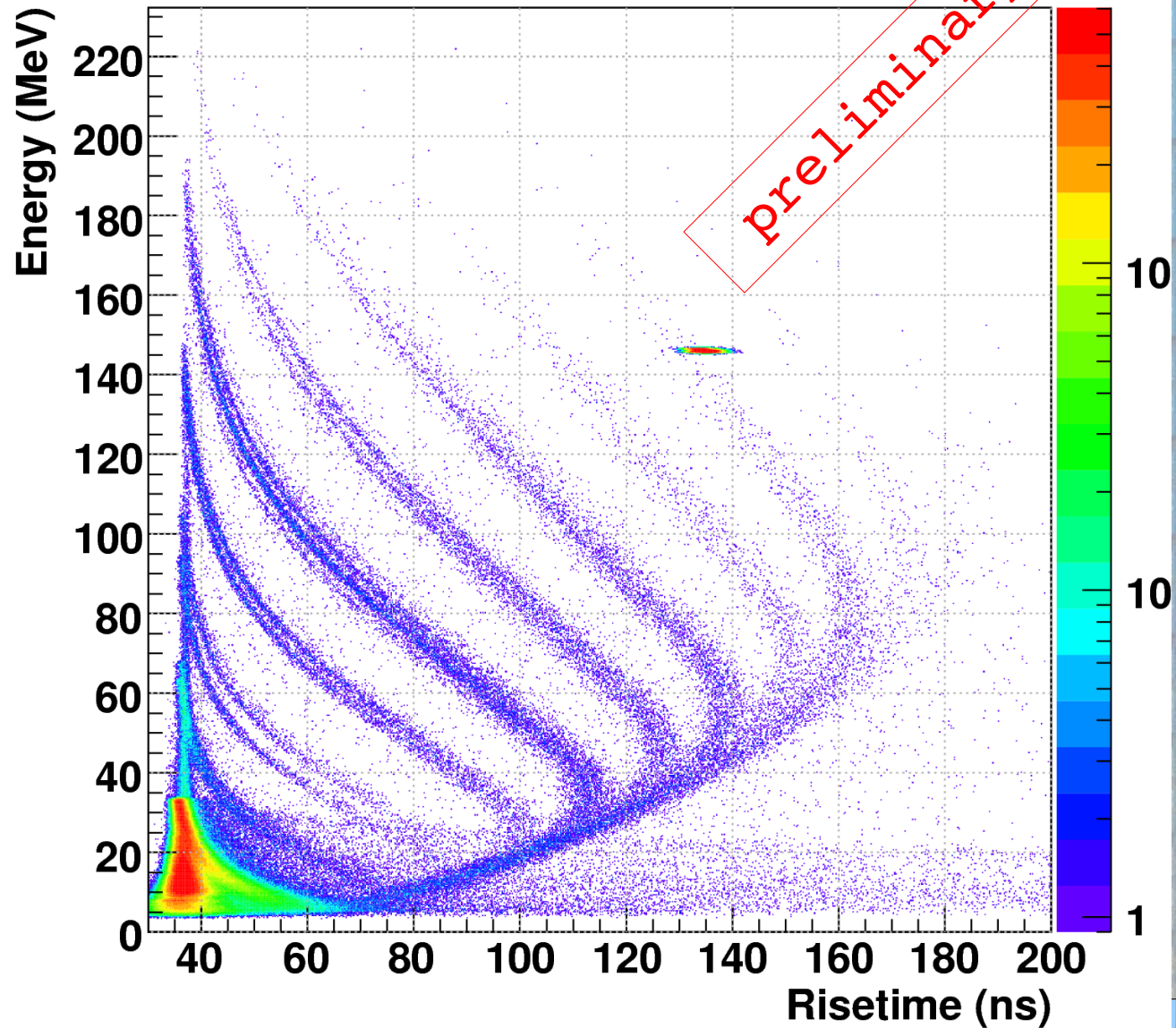
500 um detector
1.5% non-hom. (BEST)

“without” channeling
(BEST)

14 bit, 100 MS/s
digitizer

1.3 GeV full range

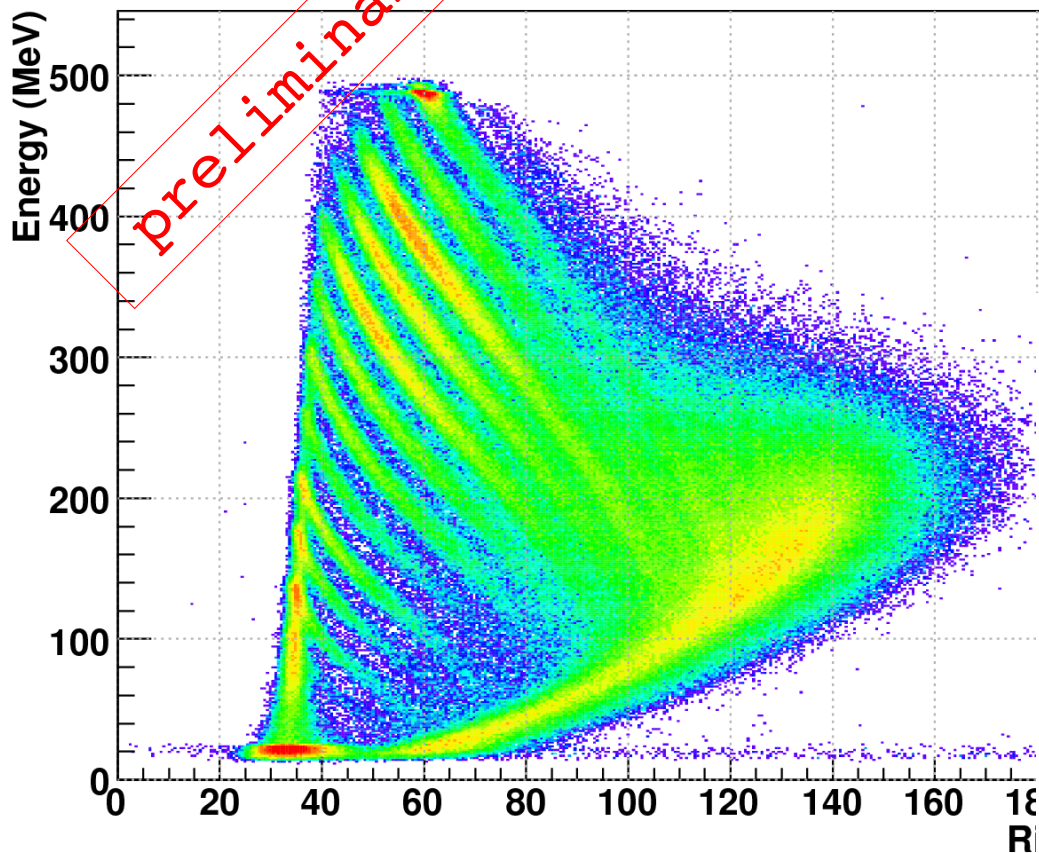
Energy vs risetime (det.G-E) - random configuration



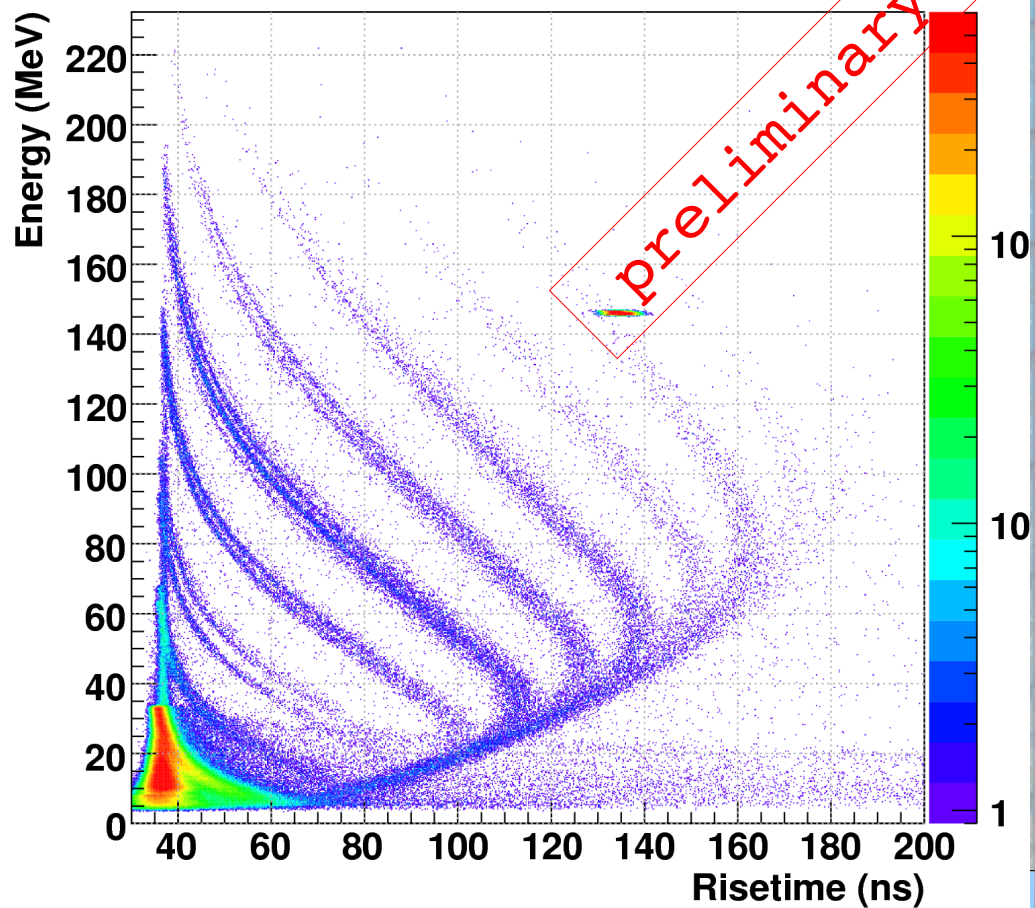
PSA in riv.73311

300 μm , 9.4% non hom.

500 μm , 1.3% non-hom.



Energy vs risetime (det.G-E) - random configuration

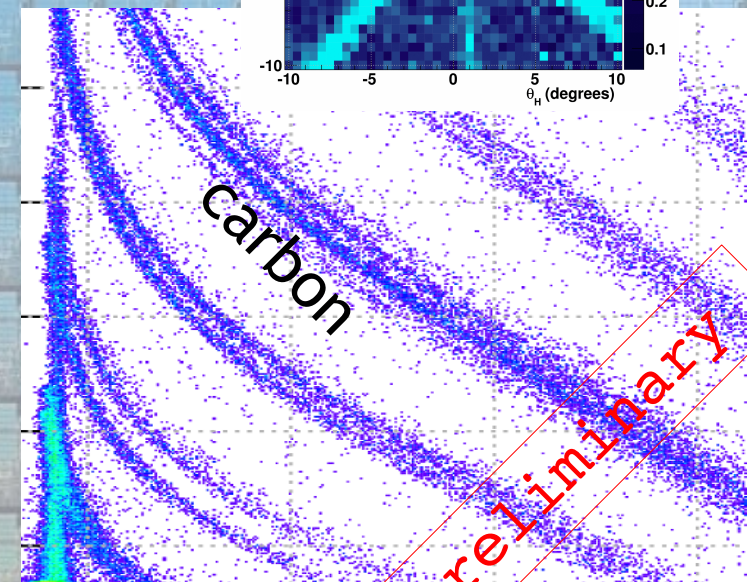
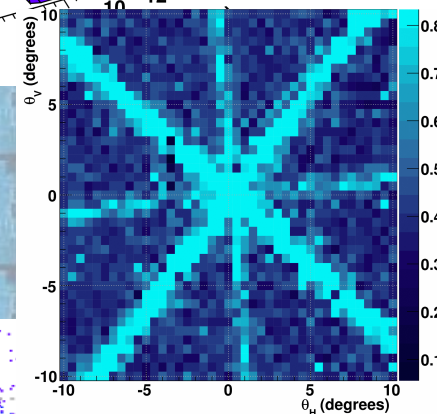
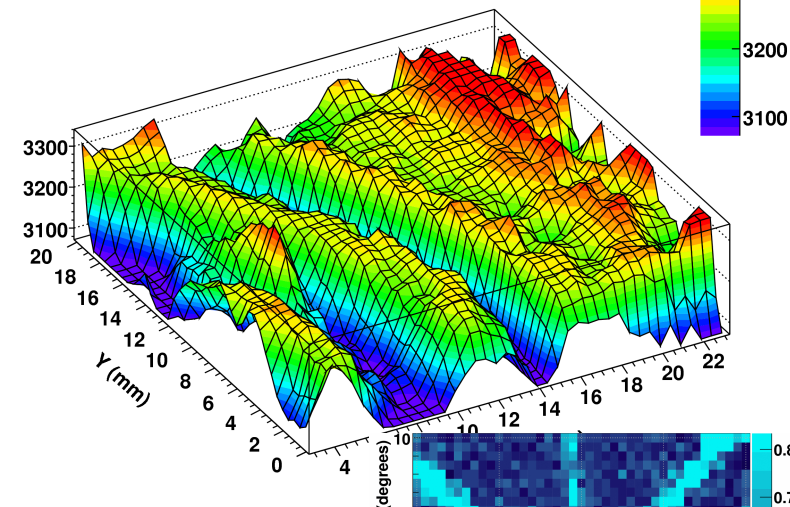


Impressive difference!

(both using non-channeling configuration, using as similar as possible overbias)

- ▶ A non-destructive method for absolute resistivity measurement in Si detectors has been discussed
- ▶ Channeling-related effects are relevant (and must be avoided!!) for both “standard” (like DE-E) and PSA applications.
- ▶ Experimental tests have been carried out in order to study channeling and to provide recipes to avoid it
- ▶ FAZIA has performed several exp. tests
- ▶ Good homogeneity (few %) + no channeling = PSA like ==>

Resistivity map (Ω cm)



L. Bardelli et al, sub. to NIM A and in prep.

